Access DB# 184441

SEARCH REQUEST FORM

Scientific and Technical Information Center

Requester's Full Name: Sin J. Lee Examiner #: 76060 Date: 4-5-2006
Art Unit: 1752 Phone Number 30 2-1333 Serial Number: 10/781,862
Mail Box and Bldg/Room Location: 9D60 (Rem.) Results Format Preferred (circle): PAPER DISK E-MAIL

If more than one search is submitted, please prioritize searches in order of need.

****

Please provide a detailed statement of the search topic, and describe as specifically as possible the subject matter to be searched. Include the elected species or structures, keywords, synonyms, acronyms, and registry numbers, and combine with the concept or utility of the invention. Define any terms that may have a special meaning. Give examples or relevant citations, authors, etc, if known. Please attach a copy of the cover sheet, pertinent claims, and abstract.

SCIENTIFIC REFERENCE BR
Sci & Tech Inf - Ctr
APR 6 RECD
Pat. & T.M. Office

Title of Invention: Plz. See B.6.

Inventors (please provide full names):

Earliest Priority Filing Date:

**For Sequence Searches Only* Please include all pertinent information (parent, child, divisional, or issued patent numbers) along with the appropriate serial number.*

Please search for a compound (A) of Cl. #1 which contains the chemical structure (or more) of formula (I) shown in Cl. #4

****

STAFF USE ONLY	Type of Search	Vendors and cost where applicable
Searcher: Usha	NA Sequence (#)	STN $ 4/9.71
Searcher Phone #:	AA Sequence (#)	Dialog
Searcher Location:	Structure (#) 1	Questel/Orbit
Date Searcher Picked Up: 4/10/06	Bibliographic	Dr.Link
Date Completed: 4/10/06	Litigation	Lexis/Nexis
Searcher Prep & Review Time: 60	Fulltext	Sequence Systems
Clerical Prep Time: 30	Patent Family	WWW/Internet
Online Time: 10	Other	Other (specify)

PTO-1590 (8-01)

UNITED STATES PATENT AND TRADEMARK OFFICE

UNITED STATES DEPARTMENT OF COMMERCE
United States Patent and Trademark Office
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P.O. Box 1450
Alexandria, Virginia 22313-1450
www.uspto.gov

Bib Data Sheet

CONFIRMATION NO. 4469

SERIAL NUMBER	FILING DATE	CLASS	GROUP ART UNIT	ATTORNEY DOCKET NO.
10/781,862	02/20/2004 RULE	430	1752	Q80021

APPLICANTS

Kazuhiro Fujimaki, Shizuoka, JAPAN;

** CONTINUING DATA **********
None SJL

** FOREIGN APPLICATIONS **********
JAPAN P.2003-043087 02/20/2003 SJL
JAPAN P.2003-194852 07/10/2003 SJL

IF REQUIRED, FOREIGN FILING LICENSE GRANTED
** 05/12/2004

Foreign Priority claimed	STATE OR	SHEETS	TOTAL	INDEPENDENT
☑ yes ☐ no 35 USC 119 (a-d) conditions met ☑ yes ☐ no ☐ Met after Allowance Verified and Acknowledged Examiner's Signature SJL Initials	COUNTRY JAPAN	DRAWING 0	CLAIMS 15	CLAIMS 4

ADDRESS
SUGHRUE MION, PLLC
2100 Pennsylvania Avenue, NW
Washington , DC
20037-3213

TITLE
Polymerizable composition

FILING FEE	FEES: Authority has been given in Paper	☐ All Fees
RECEIVED 986	No. _____ to charge/credit DEPOSIT ACCOUNT No. _____ for following:	☐ 1.16 Fees (Filing) ☐ 1.17 Fees (Processing Ext. of time) ☐ 1.18 Fees (Issue) ☐ Other _____

AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions and listings of claims in the application:

LISTING OF CLAIMS:

1. (currently amended): A polymerizable composition comprising:

(A) a monocarboxylic acid compound which causes at least one of decarboxylation and dehydration by heat;

(B) a radical initiator;

(C) a compound having at least one ethylenically unsaturated bond; and

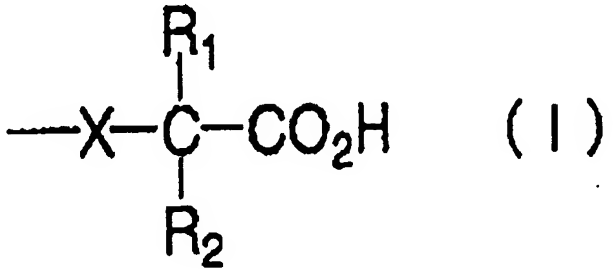
(D) an infrared ray absorber,

wherein the compound (A) and the radical initiator (B) are separate and distinct compounds from each other.

2. (original): The polymerizable composition according to claim 1, wherein the compound (A) is one which causes at least one of decarboxylation and dehydration at a temperature of 100°C to 300°C.

3. (original): The polymerizable composition according to claim 1, wherein the compound (A) is one having a structure capable of forming a 4 to 6-membered lactone ring, a 4 to 6-membered lactam ring or a 4 to 6-membered cyclic acid anhydride.

4. (currently amended): The polymerizable composition according to claim 1, wherein the compound (A) is one having ~~at least one~~a group represented by the following formula (I):



(I)

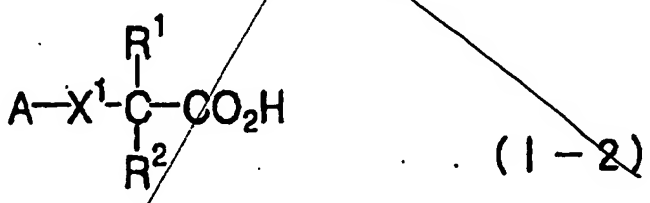
wherein:

X represents a divalent connection group selected from -O-, -S-, -SO_2-, -NH-, -N(R^3)-, and -CO-,

R^3 represents a hydrogen atom or a monovalent substituent,

R^1 and R^2 each independently represents a hydrogen atom or a monovalent substituent, provided that R^1 and R^2, or either one of R^1 and R^2 and R^3 may be taken together to form a ring structure.

5. (original): The polymerizable composition according to claim 1, wherein the compound (A) is a monocarboxylic acid compound represented by the following formula (I-2):



(I – 2)

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=> d his

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L1             1 S US20050106495/PN
                 SEL RN

     FILE 'REGISTRY' ENTERED AT 07:47:58 ON 10 APR 2006
L2            42 S E1-E42
L3               STR
L4               SCR 2043 OR 1840 OR 1918
L5               SCR 1526
L6            50 S L3 AND L5 NOT L4
L7            50 S L3 AND L5
L8        648230 S L3 AND L5 NOT L4 FUL
L9            37 S L2 AND L8

     FILE 'HCAPLUS' ENTERED AT 08:30:10 ON 10 APR 2006
L10        22987 S L9
L11            7 S L10(L)LITHOG?(3A)PRECURS?
L12           10 S L10 AND LITHOG?(3A)PRECURS?
L13           10 S L11 OR L12
L14            1 S L13 AND L1

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L16       300000 S L15  RAN=(344564-47-2,)
L17       348230 S L15 NOT L16

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L18        90086 S L16

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L21       198230 S L19 NOT L20

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L23       951630 S L21
L24       998615 S L18 OR L22 OR L23
L25       975628 S L24 NOT L10
L26           29 S L25(L)LITHOG?(3A)PRECURS?
L27           39 S L13 OR L26
L28           37 S L27 AND P/DT
L29           29 S L28 AND (1907-2003)/PRY,AY
                 SEL L29 HIT RN 1-
L30            1 S L29 AND L1


=> d que l29
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                 1137-73-1/BI OR 122-59-8/BI OR 161555-27-7/BI OR
                 35676-11-0/BI OR 3959-23-7/BI OR 60085-74-7/BI OR
                 62952-26-5/BI OR 6915-15-7/BI OR 743422-66-4/BI OR
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                 743422-73-3/BI OR 743422-74-4/BI OR 743422-75-5/BI OR
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                743422-99-3/BI OR 743423-00-9/BI OR 743423-01-0/BI OR
                743423-02-1/BI OR 743423-03-2/BI)
L3              STR

G1~C~COOH       C=O
 1  2  3       @4  5

VAR G1=O/S/SO2/N/4
NODE ATTRIBUTES:
DEFAULT MLEVEL IS ATOM
DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:
RING(S) ARE ISOLATED OR EMBEDDED
NUMBER OF NODES IS   5

STEREO ATTRIBUTES: NONE
L4              SCR 2043 OR 1840 OR 1918
L5              SCR 1526
L8        648230 SEA FILE=REGISTRY SSS FUL L3 AND L5 NOT L4
L9            37 SEA FILE=REGISTRY ABB=ON  PLU=ON  L2 AND L8
L10        22987 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L9
L11            7 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L10(L)LITHOG?(3A)PRECU
                  RS?
L12           10 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L10 AND LITHOG?(3A)PRE
                  CURS?
L13           10 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L11 OR L12
L15       648230 SEA FILE=REGISTRY ABB=ON  PLU=ON  L8 OR L8
L16       300000 SEA FILE=REGISTRY RAN=(344564-47-2,) ABB=ON  PLU=ON
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L17       348230 SEA FILE=REGISTRY ABB=ON  PLU=ON  L15 NOT L16
L18        90086 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L16
L19       348230 SEA FILE=REGISTRY ABB=ON  PLU=ON  L17 OR L17
L20       150000 SEA FILE=REGISTRY RAN=(148832-92-2,) ABB=ON  PLU=ON
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L22        53388 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L20
L23       951630 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L21
L24       998615 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L18 OR L22 OR L23
L25       975628 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L24 NOT L10
L26           29 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L25(L)LITHOG?(3A)PRECU
                  RS?
L27           39 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L13 OR L26
L28           37 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L27 AND P/DT
L29           29 SEA FILE=HCAPLUS ABB=ON  PLU=ON  L28 AND (1907-2003)/PR
                  Y,AY


=> fil hcap
FILE 'HCAPLUS' ENTERED AT 09:09:11 ON 10 APR 2006

=> d l29 1-29 ibib abs hitstr hitind

L29  ANSWER 1 OF 29  HCAPLUS  COPYRIGHT 2006 ACS on STN
```

ACCESSION NUMBER: 2005:471468 HCAPLUS
DOCUMENT NUMBER: 143:16521
TITLE: Light-sensitive **lithographic** printing plate **precursors** and process method therefor
INVENTOR(S): Suzuki, Toshitsugu; Konuma, Taro
PATENT ASSIGNEE(S): Konica Minolta Medical & Graphic, Inc., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 39 pp.
CODEN: JKXXAF
DOCUMENT TYPE: **Patent**
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2005141129	A2	20050602	JP 2003-379537	2003 1110

<--

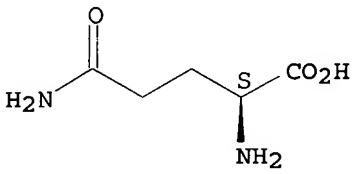
PRIORITY APPLN. INFO.: JP 2003-379537 2003 1110

<--

AB The title precursor has a photopolymerizable material layer and a protective layer on a support, wherein the protective layer contains a water-soluble polymer and diacetyl L-glutamate. The precursor provides a printing plate generating little fine dot stain on background after restarting a printer and generates reduced amount of sludge during the development process.

IT **56-85-9D**, Glutamine, diacetyl derivative
(light-sensitive **lithog.** printing plate **precursors** and process method therefor)
RN 56-85-9 HCAPLUS
CN L-Glutamine (9CI) (CA INDEX NAME)

Absolute stereochemistry.



IC ICM G03F007-11
ICS G03F007-00; G03F007-32; G03F007-38
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
ST light **lithog** printing plate **precursor**
IT **Lithographic** plates
(**precursor**, light-sensitive; light-sensitive **lithog.** printing plate **precursors** and process method therefor)
IT **56-85-9D**, Glutamine, diacetyl derivative
(light-sensitive **lithog.** printing plate **precursors** and process method therefor)

L29 ANSWER 2 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2005:259485 HCAPLUS
DOCUMENT NUMBER: 142:345190
TITLE: Photosensitive composition and **lithographic** printing plate **precursor** using the same
INVENTOR(S): Yanaka, Hiromitsu; Goto, Takahiro
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: U.S. Pat. Appl. Publ., 34 pp.
CODEN: USXXCO
DOCUMENT TYPE: **Patent**
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2005064331	A1	20050324	US 2004-947260	2004 0923
JP 2005099287	A2	20050414	JP 2003-331528	2003 0924
EP 1518704	A1	20050330	EP 2004-22792	2004 0924

R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK, HR

PRIORITY APPLN. INFO.: JP 2003-331528 A 2003 0924

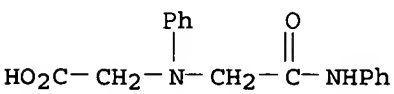
OTHER SOURCE(S): MARPAT 142:345190

AB A photosensitive composition comprises (A) polymerizable compound A{O[(CH(R1)CH(R2))mO]nC(O)C(R3):CH2}p (R1-3 = H, Me; A = polyhydric alc. residue, polyhydric phenol residue; m = 1-6; n = 1-20; p = 1-6), (B) an IR absorber, and (C) an onium salt.

IT **743422-98-2**
(photosensitive composition for **lithog.** printing plate **precursor**)

RN 743422-98-2 HCAPLUS

CN Glycine, N-[2-oxo-2-(phenylamino)ethyl]-N-phenyl- (9CI) (CA INDEX NAME)



IC ICM G03C001-492
ICS G03C001-005; G03F007-26

INCL 430270100; 430302000; 430627000

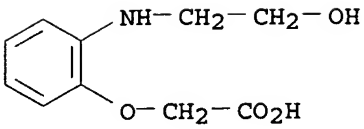
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

ST photosensitive compn **lithog** printing plate **precursor**
IT Lithographic plates
(photosensitive composition for **lithog.** printing plate **precursor**)
IT 9003-39-8, Polyvinylpyrrolidone
(Rubiscole K 30; photosensitive composition for **lithog.** printing plate **precursor**)
IT 183745-11-1 **743422-98-2** 848489-55-4
(photosensitive composition for **lithog.** printing plate **precursor**)
IT 709037-26-3
(photosensitive composition for **lithog.** printing plate **precursor**)
IT 9003-20-7D, Polyvinyl acetate, saponified 64401-02-1, Bisphenol A-ethyleneoxide adduct diacrylate 80937-22-0 91105-84-9
(photosensitive composition for **lithog.** printing plate **precursor**)

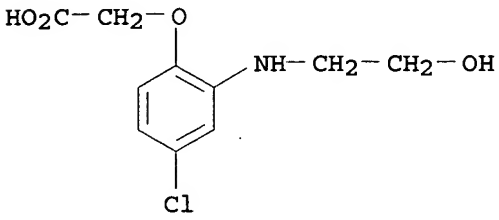
L29 ANSWER 3 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2005:209978 HCAPLUS
DOCUMENT NUMBER: 142:306465
TITLE: Photopolymerizable photoimaging composition and negatively-working directly-imaging **lithographic** printing plate **precursors** made thereof
INVENTOR(S): Fujimaki, Kazuhiro
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 81 pp.
CODEN: JKXXAF
DOCUMENT TYPE: **Patent**
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2005062478	A2	20050310	JP 2003-292453 <--	2003 0812
PRIORITY APPLN. INFO.:			JP 2003-292453 <--	2003 0812

AB The title composition contains a compound with an amino groups and hydroxy groups, an IR-absorber, a radical polymerization initiator, and ethylenic unsatd. compds. The composition shows high sensitivity and good storageability and provides highly durable layers.
IT **847564-92-5 847564-95-8**
(compound with an amino groups and hydroxy groups in composition)
RN 847564-92-5 HCAPLUS
CN Acetic acid, [2-[(2-hydroxyethyl)amino]phenoxy]- (9CI) (CA INDEX NAME)



RN 847564-95-8 HCAPLUS
CN Acetic acid, [4-chloro-2-[(2-hydroxyethyl)amino]phenoxy]- (9CI) (CA INDEX NAME)



IC ICM G03F007-004
ICS C08F002-44; G03F007-00
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
ST photopolymerizable photoimaging compn neg **lithog** printing plate **precursor**
IT Photolithography
(photopolymerizable photoimaging composition and neg.-working directly-imaging **lithog.** printing plate **precursors** therefrom)
IT Photoimaging materials
(photopolymerizable; photopolymerizable photoimaging composition and neg.-working directly-imaging **lithog.** printing plate **precursors** therefrom)
IT 93-90-3 102-71-6, uses 111-42-2, uses 120-07-0 122-96-3, 1,4-Piperazinediethanol 140-07-8 732-51-4 3040-44-6, 1-Piperidineethanol 6303-96-4 6315-51-1 13127-77-0 19721-54-1 27076-96-6 71345-85-2 89943-04-4 91645-48-6 121459-15-2, 1H-Indole-1-ethanol 847564-87-8 **847564-92-5** 847564-93-6 **847564-95-8**
(compound with an amino groups and hydroxy groups in composition)

L29 ANSWER 4 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2005:140645 HCAPLUS
DOCUMENT NUMBER: 142:228773
TITLE: **Lithographic** printing plate **precursor** and **lithographic** printing method
INVENTOR(S): Sonokawa, Koji
PATENT ASSIGNEE(S): Japan
SOURCE: U.S. Pat. Appl. Publ., 31 pp.
CODEN: USXXCO
DOCUMENT TYPE: **Patent**
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

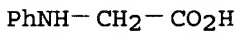
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2005037282	A1	20050217	US 2004-917354	2004 0813
JP 2005059446	A2	20050310	JP 2003-293814	2003 0815
CN 1579804	A	20050216	CN 2004-10057737	2004 0816
PRIORITY APPLN. INFO.:			JP 2003-293814 A	2003 0815

OTHER SOURCE(S): MARPAT 142:228773

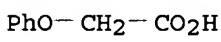
AB A **lithog.** printing plate **precursor** comprises: a support; and an image recording layer containing (A) an IR absorbing agent, (B) a polymerization initiator, (C) a polymerizable compound and (D) a compound having a carboxylate group and being removable with at least one of a printing ink and a fountain solution

IT **103-01-5 122-59-8 1137-73-1 3959-23-7 35676-11-0 161555-27-7 743422-80-2 743422-81-3 743422-82-4 743422-92-6 743422-98-2**
(compound having a carboxylate group; **lithog.** printing plate **precursor** containing)

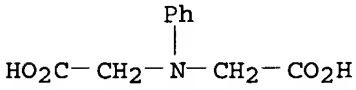
RN 103-01-5 HCAPLUS
CN Glycine, N-phenyl- (6CI, 7CI, 8CI, 9CI) (CA INDEX NAME)



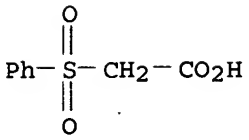
RN 122-59-8 HCAPLUS
CN Acetic acid, phenoxy- (8CI, 9CI) (CA INDEX NAME)



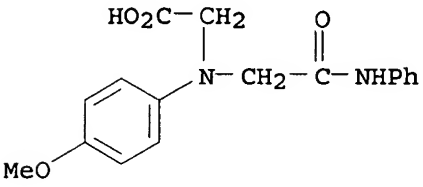
RN 1137-73-1 HCAPLUS
CN Glycine, N-(carboxymethyl)-N-phenyl- (9CI) (CA INDEX NAME)



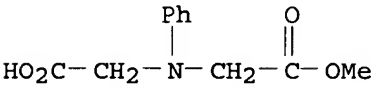
RN 3959-23-7 HCAPLUS
CN Acetic acid, (phenylsulfonyl)- (6CI, 8CI, 9CI) (CA INDEX NAME)



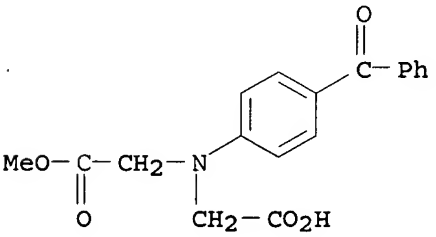
RN 35676-11-0 HCAPLUS
CN Glycine, N-(4-methoxyphenyl)-N-[2-oxo-2-(phenylamino)ethyl]- (9CI) (CA INDEX NAME)



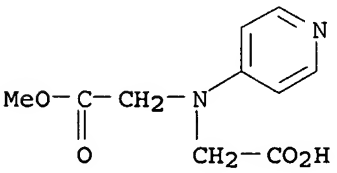
RN 161555-27-7 HCAPLUS
CN Glycine, N-(carboxymethyl)-N-phenyl-, 1-methyl ester (9CI) (CA INDEX NAME)



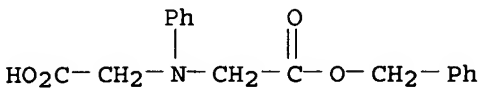
RN 743422-80-2 HCAPLUS
CN Glycine, N-(4-benzoylphenyl)-N-(carboxymethyl)-, 1-methyl ester (9CI) (CA INDEX NAME)



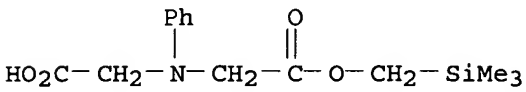
RN 743422-81-3 HCAPLUS
CN Glycine, N-(carboxymethyl)-N-4-pyridinyl-, 1-methyl ester (9CI) (CA INDEX NAME)



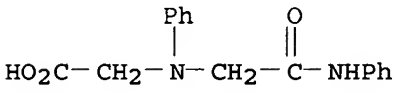
RN 743422-82-4 HCAPLUS
CN Glycine, N-(carboxymethyl)-N-phenyl-, 1-(phenylmethyl) ester (9CI) (CA INDEX NAME)



RN 743422-92-6 HCAPLUS
CN Glycine, N-(carboxymethyl)-N-phenyl-, 1-[(trimethylsilyl)methyl] ester (9CI) (CA INDEX NAME)



RN 743422-98-2 HCAPLUS
CN Glycine, N-[2-oxo-2-(phenylamino)ethyl]-N-phenyl- (9CI) (CA INDEX NAME)



IC ICM G03F007-00
INCL 430270100; 430302000
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
ST **lithog** printing plate **precursor**
IT Lithographic plates
(**lithog.** printing plate **precursor** and **lithog.** printing method)
IT **103-01-5 122-59-8** 334-48-5, Decanoic acid 528-44-9, 1,2,4-Benzenetricarboxylic acid **1137-73-1** **3959-23-7** 4282-31-9, 2,5-Thiophenedicarboxylic acid 16024-56-9 16024-58-1 **35676-11-0 161555-27-7** **743422-80-2 743422-81-3 743422-82-4** **743422-92-6 743422-98-2** 844499-45-2 844499-46-3
(compound having a carboxylate group; **lithog.** printing plate **precursor** containing)

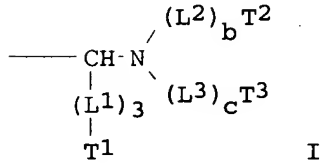
L29 ANSWER 5 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2005:140644 HCAPLUS
DOCUMENT NUMBER: 142:228772
TITLE: Heat-sensitive **lithographic** printing plate **precursor**
INVENTOR(S): Loccufier, Johan; Groenedaal, Bert; Van Damme, Marc; Van Aert, Huub
PATENT ASSIGNEE(S): Agfa-Gevaert, Belg.
SOURCE: U.S. Pat. Appl. Publ., 15 pp.
CODEN: USXXCO
DOCUMENT TYPE: **Patent**

LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2005037280	A1	20050217	US 2004-916154	2004 0811
EP 1506858	A2	20050216	EP 2004-103278 <--	2004 0709
EP 1506858	A3	20051012		
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK, HR				
JP 2005062875	A2	20050310	JP 2004-234783	2004 0811

PRIORITY APPLN. INFO.:
EP 2003-102522 A 2003 0813 <--
US 2003-499428P P 2003 0902 <--

GI



I

AB A heat-sensitive **lithog.** printing plate **precursor** is disclosed which comprises a hydrophilic support and an oleophilic coating comprising an IR absorbing agent and a developer soluble polymer which comprises a phenolic monomeric unit wherein the Ph group of the phenolic monomeric unit is substituted by a group I (L1,3 are linking groups; a, b and c are 0 or 1; and T1,3 are terminal groups), which is covalently linked to a carbon atom of the Ph group . The polymer, substituted by the group I, increases the chemical resistance of the coating.

IT **142-73-4DP**, reaction products with novolac resin (heat-sensitive **lithog.** printing plate **precursor** containing)
RN 142-73-4 HCAPLUS
CN Glycine, N-(carboxymethyl)- (9CI) (CA INDEX NAME)

$HO_2C-CH_2-NH-CH_2-CO_2H$

IC ICM G03C001-76
INCL 430270100
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35, 38
ST heat sensitive **lithog** printing plate **precursor**
IT Optical materials
(IR absorbers; heat-sensitive **lithog.** printing plate **precursor** containing)
IT IR materials
(absorbers; heat-sensitive **lithog.** printing plate **precursor** containing)
IT Lithographic plates
(heat-sensitive **lithog.** printing plate **precursor**)
IT Phenolic resins, uses
(novolak; heat-sensitive **lithog.** printing plate **precursor** containing)
IT 50-00-0DP, Formaldehyde, reaction products with novolac resin
100-46-9DP, Benzylamine, reaction products with novolac resin
109-83-1DP, reaction products with novolac resin 110-91-8DP, Morpholine, reaction products with novolac resin 123-75-1DP, Pyrrolidine, reaction products with novolac resin 124-02-7P
141-43-5DP, 2-Aminoethanol, reaction products with novolac resin
142-73-4DP, reaction products with novolac resin
100346-90-5DP, Alnovol SPN 452, terminated
(heat-sensitive **lithog.** printing plate **precursor** containing)
IT 844476-75-1, Bakelite 6866LB03
(heat-sensitive **lithog.** printing plate **precursor** containing)

L29 ANSWER 6 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2005:36461 HCAPLUS
DOCUMENT NUMBER: 142:123227
TITLE: **Lithographic** printing plate **precursor** and **lithographic** printing method
INVENTOR(S): Mitsumoto, Tomoyoshi; Makino, Naonori
PATENT ASSIGNEE(S): Japan
SOURCE: U.S. Pat. Appl. Publ., 28 pp.
CODEN: USXXCO
DOCUMENT TYPE: **Patent**
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2005008971	A1	20050113	US 2004-885807	2004 0708
JP 2005041206	A2	20050217	JP 2004-175090 <--	2004

				0614
			<--	
CN 1577087	A	20050209	CN 2004-10063829	
				2004
				0712
			<--	
PRIORITY APPLN. INFO.:			JP 2003-272909	A
				2003
				0710
			<--	
			JP 2004-175090	A
				2004
				0614

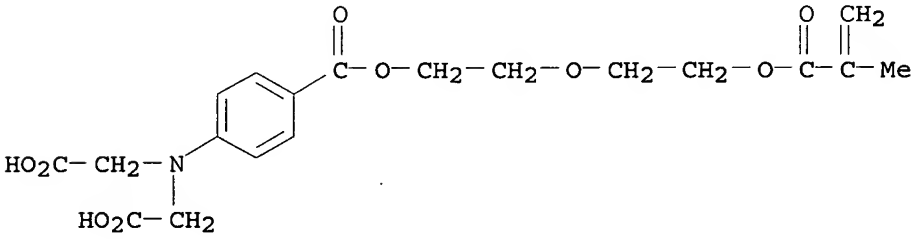
OTHER SOURCE(S): MARPAT 142:123227

AB A **lithog.** printing plate **precursor** comprises: a support; an undercoat layer; and an image recording layer containing a polymerization initiator, a polymerizable compound and an IR ray absorbing agent, the image recording layer being removable with at least one of a printing ink and a fountain solution, in this order, wherein the undercoat layer contains a compound having (a) an ethylenically unsatd. bond and (b) a functional group capable of adsorbing to a surface of the support.

IT **823814-93-3 823814-94-4**
(**lithog.** printing plate **precursor** containing)

RN 823814-93-3 HCAPLUS

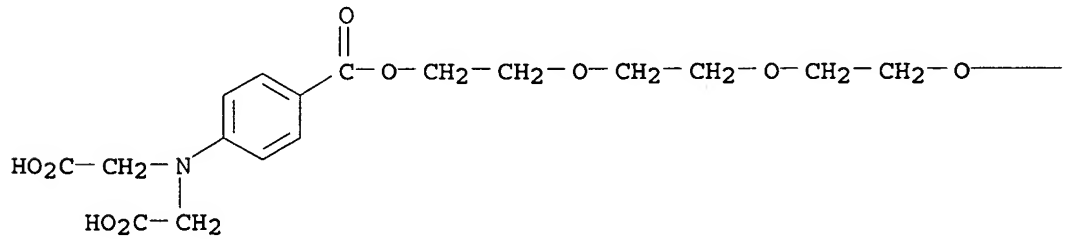
CN Benzoic acid, 4-[bis(carboxymethyl)amino]-, 1-[2-[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethoxy]ethyl] ester (9CI) (CA INDEX NAME)



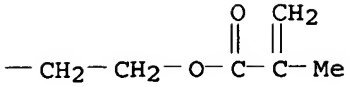
RN 823814-94-4 HCAPLUS

CN Benzoic acid, 4-[bis(carboxymethyl)amino]-, 1-(14-methyl-13-oxo-3,6,9,12-tetraoxapentadec-14-en-1-yl) ester (9CI) (CA INDEX NAME)

PAGE 1-A



PAGE 1-B



IC ICM G03C001-76
INCL 430270100
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
ST **lithog** printing plate **precursor**
IT Lithographic plates
(**lithog.** printing plate **precursor** and **lithog.** printing method)
IT 52297-22-0 155914-99-1 **823814-93-3 823814-94-4**
823814-95-5 823814-96-6 823814-97-7
(**lithog.** printing plate **precursor** containing)

L29 ANSWER 7 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2004:837357 HCAPLUS
DOCUMENT NUMBER: 141:340428
TITLE: Photosensitive composition and **lithographic** printing plate **precursor**
INVENTOR(S): Murota, Yasubumi
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Eur. Pat. Appl., 39 pp.
CODEN: EPXXDW
DOCUMENT TYPE: **Patent**
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

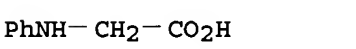
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 1467250	A2	20041013	EP 2004-8640	2004 0408
EP 1467250	A3	20050608		
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK, HR				
JP 2004309976	A2	20041104	JP 2003-106677	2003 0410
US 2004202957	A1	20041014	US 2004-819184	2004 0407

PRIORITY APPLN. INFO.: JP 2003-106677 A 2003 0410
OTHER SOURCE(S): MARPAT 141:340428
AB Disclosed is a photosensitive composition for litog. printing plate,

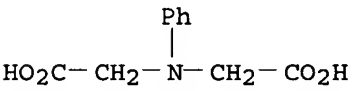
containing an IR absorber, a borate compound, a polymerizable compound, a binder polymer, and a compound having a weight average mol. weight of ≤ 3,000 and containing at least one carboxylic acid group. According to the invention, it is possible to provide a photosensitive composition having high sensitivity and good storage stability (unprocessed stock storability) and useful as a photosensitive layer of a neg. working **lithog.** printing plate **precursor.** Also, it is possible to provide a neg. working **lithog.** printing plate **precursor** capable of being recorded with high sensitivity by IR laser and having excellent storage stability (unprocessed stock storability) and printing resistance.

IT **103-01-5 1137-73-1**
(photosensitive composition and **lithog.** printing plate **precursor**)

RN 103-01-5 HCAPLUS
CN Glycine, N-phenyl- (6CI, 7CI, 8CI, 9CI) (CA INDEX NAME)



RN 1137-73-1 HCAPLUS
CN Glycine, N-(carboxymethyl)-N-phenyl- (9CI) (CA INDEX NAME)



IC ICM G03F007-004
ICS B41C001-10

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38

ST photosensitive compn **lithog** printing plate **precursor**

IT Lithographic plates
(neg.-working presensitized; photosensitive composition and **lithog.** printing plate **precursor**)

IT Polyurethanes, uses
(photosensitive composition and **lithog.** printing plate **precursor**)

IT 67653-78-5P, Dipentaerythritol hexaacrylate, homopolymer 181192-15-4P
(photosensitive composition and **lithog.** printing plate **precursor**)

IT 88-99-3, 1,2-Benzenedicarboxylic acid, uses **103-01-5** 119-80-2 528-44-9, 1,2,4-Benzenetricarboxylic acid **1137-73-1** 4282-31-9, 2,5-Thiophenedicarboxylic acid 15522-59-5 29570-58-9, Dipentaerythritol hexaacrylate 91105-84-9 183745-11-1 191726-69-9 199127-03-2 293329-29-0 658705-94-3 676349-80-7
(photosensitive composition and **lithog.** printing plate **precursor**)

L29 ANSWER 8 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2004:753228 HCAPLUS
DOCUMENT NUMBER: 141:285830
TITLE: Developing solution for **lithographic**

printing plate **precursor**, and method for preparing lithographic printing plate

INVENTOR(S): Takamiya, Shuichi
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Eur. Pat. Appl., 64 pp.
CODEN: EPXXDW

DOCUMENT TYPE: **Patent**
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

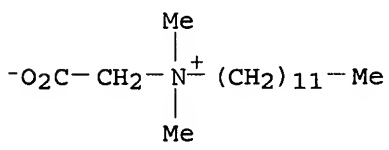
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 1457836	A2	20040915	EP 2004-5605	2004 0309
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK				
JP 2004271985	A2	20040930	JP 2003-63650	2003 0310
US 2004185371	A1	20040923	US 2004-795369	2004 0309
PRIORITY APPLN. INFO.:			JP 2003-63650 A	2003 0310

OTHER SOURCE(S): MARPAT 141:285830

AB The present invention relates to an alkaline developing solution for development of a presensitized plate for use in making a lithog. printing plate, which developing solution comprises a polyoxyalkylene adduct of alkylene diamine, and at least one selected from the group consisting of anionic surfactants and amphoteric surfactants; a method for preparing a lithog. printing plate comprising the steps of light-exposing a presensitized plate for use in making a lithog. printing plate, and developing the light-exposed plate with the above alkaline developing solution

IT **683-10-3**
(surfactant; developing solution for **lithog.** printing plate **precursor** containing)

RN 683-10-3 HCAPLUS
CN 1-Dodecanaminium, N-(carboxymethyl)-N,N-dimethyl-, inner salt (9CI) (CA INDEX NAME)



IC ICM G03F007-30
ICS G03F007-32

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
ST developing soln **lithog** printing plate **precursor** surfactant
IT Surfactants
(amphoteric; developing solution for **lithog.** printing plate **precursor** containing)
IT Surfactants
(anionic; developing solution for **lithog.** printing plate **precursor** containing)
IT Lithographic plates
(developing solution for **lithog.** printing plate **precursor**)
IT 151-21-3, uses **683-10-3** 3546-96-1 9003-11-6D, Oxirane-methyloxirane copolymer, r.p. with ethylenediamine 14960-06-6 26545-58-4 27014-42-2 27176-87-0 31094-14-1 40032-04-0 40382-75-0 59269-54-4 757955-10-5 757955-13-8 757955-18-3
(surfactant; developing solution for **lithog.** printing plate **precursor** containing)

L29 ANSWER 9 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2004:700261 HCAPLUS
DOCUMENT NUMBER: 141:215685
TITLE: Polymerizable composition and **lithographic** printing plate **precursor**
INVENTOR(S): ~~Fujimaki~~, Kazuhiro
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Eur. Pat. Appl., 96 pp.
CODEN: EPXXDW
DOCUMENT TYPE: **Patent**
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

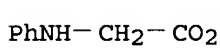
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 1449651	A2	20040825	EP 2004-3844	2004 0220
			<--	
EP 1449651	A3	20050504		
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK				
JP 2004310000	A2	20041104	JP 2003-194852	2003 0710
			<--	
CN 1525249	A	20040901	CN 2004-10007009	2004 0220
			<--	
US 2005106495	A1	20050519	US 2004-781862	2004 0220
			<--	
PRIORITY APPLN. INFO.:			JP 2003-43087	A

2003
0220
<--
JP 2003-194852 A
2003
0710
<--

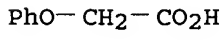
AB A polymerizable composition comprises: (A) a compound which causes at least one of decarboxylation and dehydration by heat; (B) a radical initiator; (C) a compound having at least one ethylenically unsatd. bond; and (D) an IR ray absorber and a **lithog.** printing plate **precursor** comprising a support and a recording layer comprising said polymerizable composition

IT **103-01-5 122-59-8 1137-73-1**
3959-23-7 6915-15-7 35676-11-0
60085-74-7 161555-27-7 743422-66-4
743422-67-5 743422-68-6 743422-69-7
743422-70-0 743422-73-3 743422-74-4
743422-76-6 743422-77-7 743422-78-8
743422-79-9 743422-80-2 743422-81-3
743422-82-4 743422-83-5 743422-84-6
743422-85-7 743422-86-8 743422-88-0
743422-90-4 743422-92-6 743422-93-7
743422-96-0 743422-98-2 743422-99-3
743423-00-9 743423-01-0 743423-02-1
743423-03-2
(polymerizable composition and **lithog.** printing plate **precursor** containing)

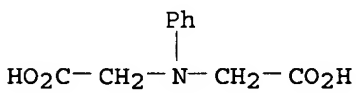
RN 103-01-5 HCAPLUS
CN Glycine, N-phenyl- (6CI, 7CI, 8CI, 9CI) (CA INDEX NAME)



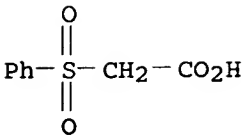
RN 122-59-8 HCAPLUS
CN Acetic acid, phenoxy- (8CI, 9CI) (CA INDEX NAME)



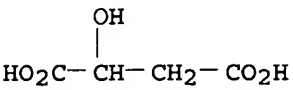
RN 1137-73-1 HCAPLUS
CN Glycine, N-(carboxymethyl)-N-phenyl- (9CI) (CA INDEX NAME)



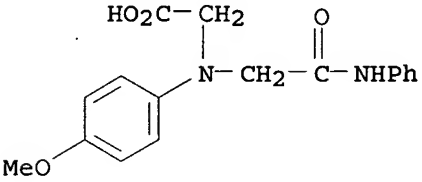
RN 3959-23-7 HCAPLUS
CN Acetic acid, (phenylsulfonyl)- (6CI, 8CI, 9CI) (CA INDEX NAME)



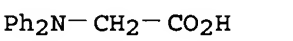
RN 6915-15-7 HCAPLUS
CN Butanedioic acid, hydroxy- (9CI) (CA INDEX NAME)



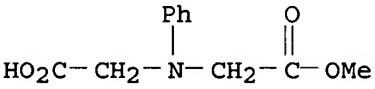
RN 35676-11-0 HCAPLUS
CN Glycine, N-(4-methoxyphenyl)-N-[2-oxo-2-(phenylamino)ethyl]- (9CI) (CA INDEX NAME)



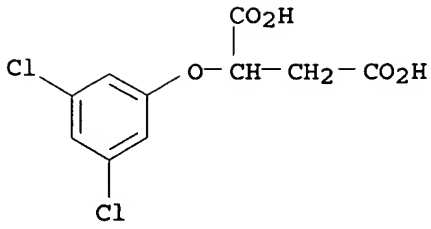
RN 60085-74-7 HCAPLUS
CN Glycine, N,N-diphenyl- (9CI) (CA INDEX NAME)



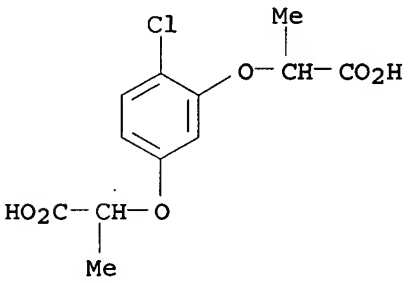
RN 161555-27-7 HCAPLUS
CN Glycine, N-(carboxymethyl)-N-phenyl-, 1-methyl ester (9CI) (CA INDEX NAME)



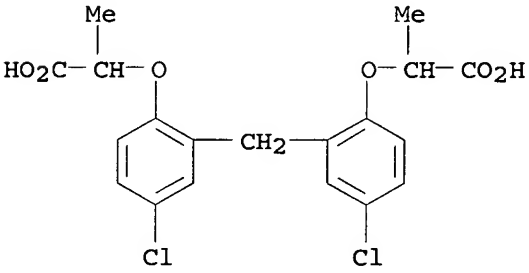
RN 743422-66-4 HCAPLUS
CN Butanedioic acid, (3,5-dichlorophenoxy)- (9CI) (CA INDEX NAME)



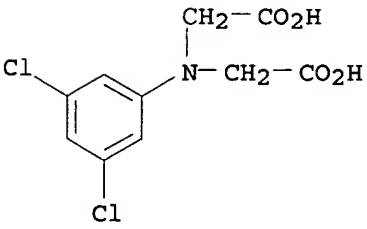
RN 743422-67-5 HCAPLUS
CN Propanoic acid, 2,2'-[(4-chloro-1,3-phenylene)bis(oxy)]bis- (9CI) (CA INDEX NAME)



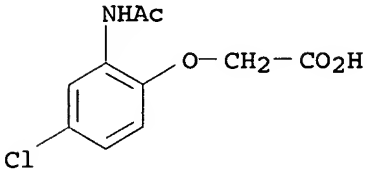
RN 743422-68-6 HCAPLUS
CN Propanoic acid, 2,2'-[methylenebis[(4-chloro-2,1-phenylene)oxy]]bis- (9CI) (CA INDEX NAME)



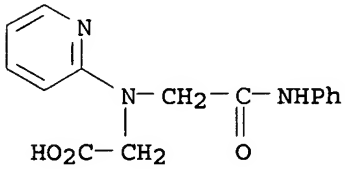
RN 743422-69-7 HCAPLUS
CN Glycine, N-(carboxymethyl)-N-(3,5-dichlorophenyl)- (9CI) (CA INDEX NAME)



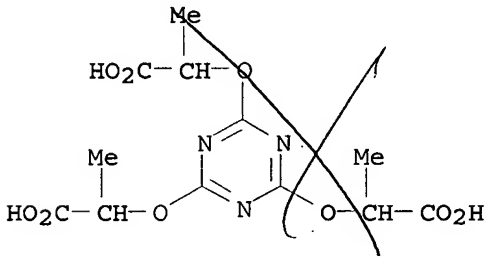
RN 743422-70-0 HCAPLUS
CN Acetic acid, [2-(acetylamino)-4-chlorophenoxy]- (9CI) (CA INDEX NAME)



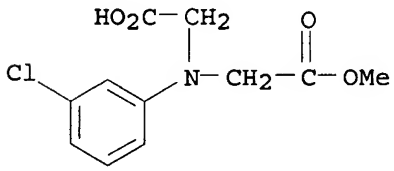
RN 743422-73-3 HCAPLUS
CN Glycine, N-[2-oxo-2-(phenylamino)ethyl]-N-2-pyridinyl- (9CI) (CA INDEX NAME)



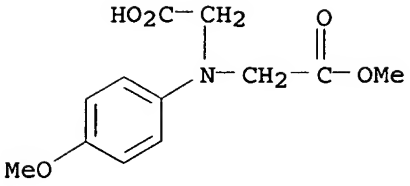
RN 743422-74-4 HCAPLUS
CN Propanoic acid, 2,2',2''-[1,3,5-triazine-2,4,6-triyltris(oxy)]tris- (9CI) (CA INDEX NAME)



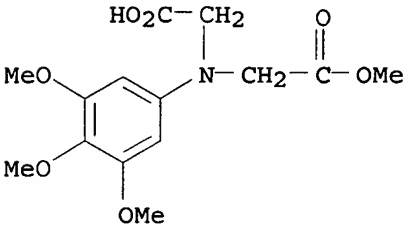
RN 743422-76-6 HCAPLUS
CN Glycine, N-(carboxymethyl)-N-(3-chlorophenyl)-, 1-methyl ester (9CI) (CA INDEX NAME)



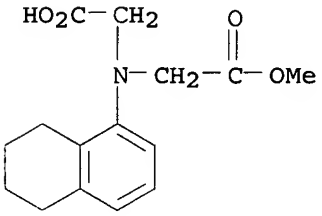
RN 743422-77-7 HCAPLUS
CN Glycine, N-(carboxymethyl)-N-(4-methoxyphenyl)-, 1-methyl ester (9CI) (CA INDEX NAME)



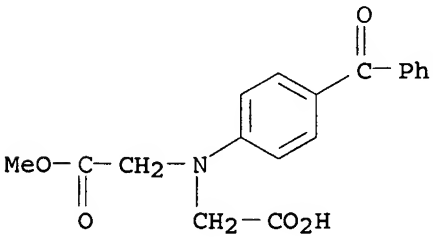
RN 743422-78-8 HCAPLUS
CN Glycine, N-(carboxymethyl)-N-(3,4,5-trimethoxyphenyl)-, 1-methyl ester (9CI) (CA INDEX NAME)



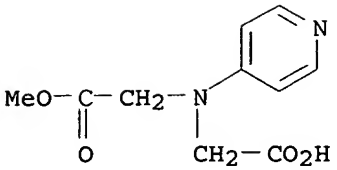
RN 743422-79-9 HCAPLUS
CN Glycine, N-(carboxymethyl)-N-(5,6,7,8-tetrahydro-1-naphthalenyl)-, 1-methyl ester (9CI) (CA INDEX NAME)



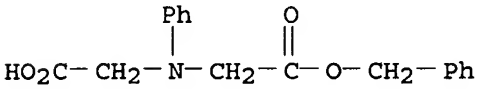
RN 743422-80-2 HCAPLUS
CN Glycine, N-(4-benzoylphenyl)-N-(carboxymethyl)-, 1-methyl ester (9CI) (CA INDEX NAME)



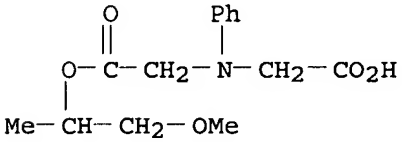
RN 743422-81-3 HCAPLUS
CN Glycine, N-(carboxymethyl)-N-4-pyridinyl-, 1-methyl ester (9CI) (CA INDEX NAME)



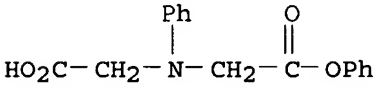
RN 743422-82-4 HCAPLUS
CN Glycine, N-(carboxymethyl)-N-phenyl-, 1-(phenylmethyl) ester (9CI) (CA INDEX NAME)



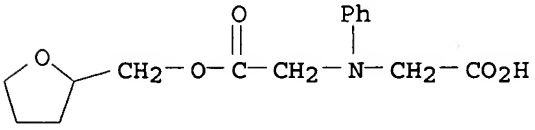
RN 743422-83-5 HCAPLUS
CN Glycine, N-(carboxymethyl)-N-phenyl-, 1-(2-methoxy-1-methylethyl) ester (9CI) (CA INDEX NAME)



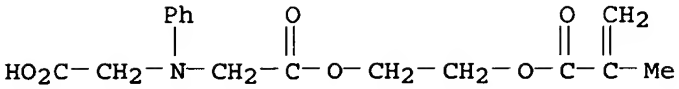
RN 743422-84-6 HCAPLUS
CN Glycine, N-(carboxymethyl)-N-phenyl-, 1-phenyl ester (9CI) (CA INDEX NAME)



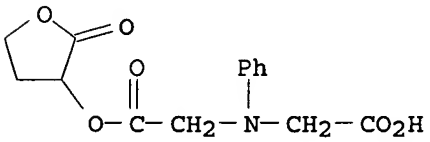
RN 743422-85-7 HCAPLUS
CN Glycine, N-(carboxymethyl)-N-phenyl-, 1-[(tetrahydro-2-furanyl)methyl] ester (9CI) (CA INDEX NAME)



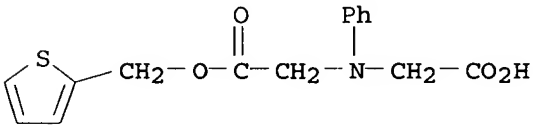
RN 743422-86-8 HCAPLUS
CN Glycine, N-(carboxymethyl)-N-phenyl-, 1-[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl] ester (9CI) (CA INDEX NAME)



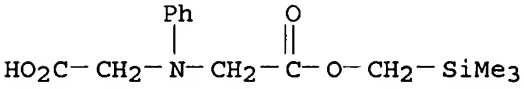
RN 743422-88-0 HCAPLUS
CN Glycine, N-(carboxymethyl)-N-phenyl-, 1-(tetrahydro-2-oxo-3-furanyl) ester (9CI) (CA INDEX NAME)



RN 743422-90-4 HCAPLUS
CN Glycine, N-(carboxymethyl)-N-phenyl-, 1-(2-thienylmethyl) ester (9CI) (CA INDEX NAME)



RN 743422-92-6 HCAPLUS
CN Glycine, N-(carboxymethyl)-N-phenyl-, 1-[(trimethylsilyl)methyl] ester (9CI) (CA INDEX NAME)



RN 743422-93-7 HCAPLUS
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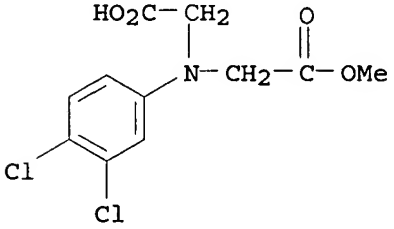
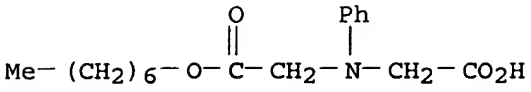
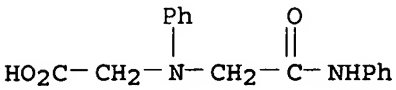


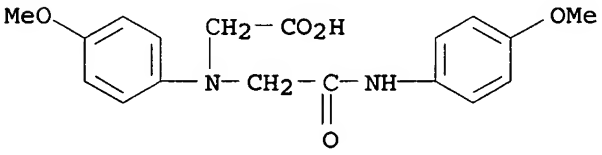
RN 743422-96-0 HCAPLUS
CN Glycine, N-(carboxymethyl)-N-phenyl-, 1-heptyl ester (9CI) (CA INDEX NAME)



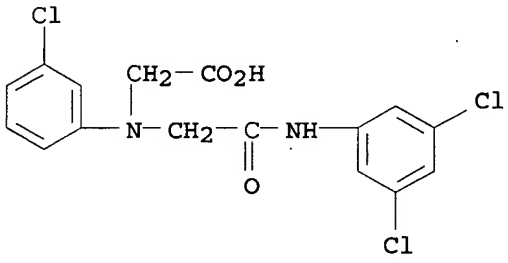
RN 743422-98-2 HCAPLUS
CN Glycine, N-[2-oxo-2-(phenylamino)ethyl]-N-phenyl- (9CI) (CA INDEX NAME)



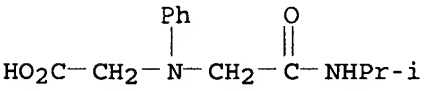
RN 743422-99-3 HCAPLUS
CN Glycine, N-(4-methoxyphenyl)-N-[2-[(4-methoxyphenyl)amino]-2-oxoethyl]- (9CI) (CA INDEX NAME)



RN 743423-00-9 HCAPLUS
CN Glycine, N-(3-chlorophenyl)-N-[2-[(3,5-dichlorophenyl)amino]-2-oxoethyl]- (9CI) (CA INDEX NAME)



RN 743423-01-0 HCAPLUS
CN Glycine, N-[2-[(1-methylethyl)amino]-2-oxoethyl]-N-phenyl- (9CI) (CA INDEX NAME)



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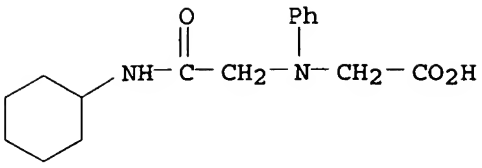
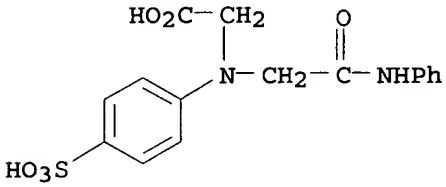
CN Glycine, N-[2-(cyclohexylamino)-2-oxoethyl]-N-phenyl- (9CI) (CA INDEX NAME)



RN 743423-03-2 HCAPLUS
CN Glycine, N-[2-oxo-2-(phenylamino)ethyl]-N-(4-sulfophenyl)- (9CI) (CA INDEX NAME)



IC ICM B41C001-10
ICS G03F007-004
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
ST polymerizable compn **lithog** printing plate **precursor**
IT Dyes
(IR-absorbing; polymerizable composition and **lithog.** printing plate **precursor**)
IT Lithographic plates
(polymerizable composition and **lithog.** printing plate **precursor**)
IT **103-01-5 122-59-8 1137-73-1**
3959-23-7 6915-15-7 35676-11-0
60085-74-7 62952-26-5 **161555-27-7**
743422-66-4 743422-67-5 743422-68-6
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743422-81-3 743422-82-4 743422-83-5
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743422-98-2 743422-99-3 743423-00-9
743423-01-0 743423-02-1 743423-03-2
(polymerizable composition and **lithog.** printing plate **precursor** containing)

L29 ANSWER 10 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2004:392172 HCAPLUS
DOCUMENT NUMBER: 140:397389
TITLE: Hetero-substituted aryl acetic acid co-initiators for IR-sensitive compositions for manufacturing negative-working printing plate precursors
INVENTOR(S): Munnelly, Heidi M.; West, Paul R.; Timpe,

Hans-joachim; Muller, Ursula; Huang, Jianbing
PATENT ASSIGNEE(S): USA
SOURCE: U.S. Pat. Appl. Publ., 12 pp.
CODEN: USXXCO
DOCUMENT TYPE: **Patent**
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 4
PATENT INFORMATION:

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US 2004091811	A1	20040513	US 2002-283757	2002 1030
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WO 2003-US33820 W
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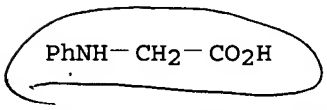
OTHER SOURCE(S): MARPAT 140:397389

AB The invention relates to an IR-sensitive composition comprising, in addition to a polymeric binder, a free radical polymerizable system consisting of at least one member selected from unsatd. free radical polymerizable monomers, oligomers which are free radical polymerizable, and polymers containing C=C bonds in the back bone and/or in the side chain groups and an initiator system, wherein the initiator system comprises the following components: (a) at least one material capable of absorbing IR radiation, (b) at least one compound capable of producing radicals and (c) at least one hereto-substituted arylacetic acid co-initiator compound such as phenoxyacetic acid, (2-methoxyphenoxy)acetic acid, etc.

IT **103-01-5**, N-Phenylglycine **122-59-8**, Phenoxyacetic acid
(hetero-substituted aryl acetic acid co-initiators for ir-sensitive compns.)

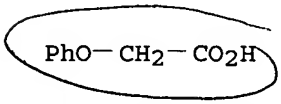
RN 103-01-5 HCAPLUS

CN Glycine, N-phenyl- (6CI, 7CI, 8CI, 9CI) (CA INDEX NAME)



RN 122-59-8 HCAPLUS

CN Acetic acid, phenoxy- (8CI, 9CI) (CA INDEX NAME)



IC ICM G03F007-038
ICS G03F007-11

INCL 430270100; 430273100; 430281100; 430286100; 430302000; 430309000; 430434000; 430494000; 430944000; 430945000

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

IT **Lithographic** plates
(IR-sensitive, **precursor**; hetero-substituted aryl acetic acid co-initiators for ir-sensitive compns. for manufacturing neg.-working printing plate precursors)

IT 87-51-4, Indole-3-acetic acid, uses **103-01-5**, N-Phenylglycine **122-59-8**, Phenoxyacetic acid 1878-85-9, (2-Methoxyphenoxy)acetic acid 95735-63-0,

3,4-Dimethoxyphenylthioacetic acid
(hetero-substituted aryl acetic acid co-initiators for ir-sensitive compns.)

L29 ANSWER 11 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2004:305338 HCAPLUS
DOCUMENT NUMBER: 140:329569
TITLE: **Lithographic** printing plate **precursor** and method for printing plate making using the same
INVENTOR(S): Oshima, Yasuhito; Makino, Naonori
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 61 pp.
CODEN: JKXXAF
DOCUMENT TYPE: **Patent**
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004114440	A2	20040415	JP 2002-279573	2002 0925

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PRIORITY APPLN. INFO.: JP 2002-279573 2002 0925

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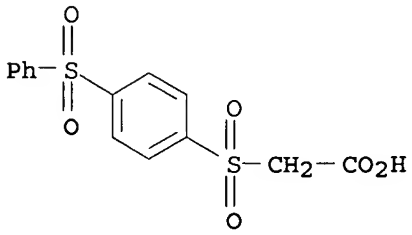
AB The title printing plate precursor has an image-forming layer on a hydrophilic support, wherein the image-forming layer contains a salt of a heat-sensitive carboxylic acid and di- or tetraacid organic base and ethylenic unsatd. compds. having carbonyl groups, and a light-to-heat converting compound The printing plate precursor shows the high sensitivity and provides printing plate of good printing resistance.

IT **97649-40-6D**, [4-(Phenylsulfonyl)phenylsulfonyl]acetic acid, salt with amine
(**lithog.** printing plate **precursor** and method for printing plate making using the same)
RN 97649-40-6 HCAPLUS
CN Acetic acid, [[4-(phenylsulfonyl)phenyl]sulfonyl]- (9CI) (CA INDEX NAME)



IC ICM B41N001-14
ICS B41C001-055; G03F007-00; G03F007-004
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

ST **lithog** printing plate **precursor**
IT Lithographic plates
(**lithog.** printing plate **precursor** and
method for printing plate making using the same)
IT 2451-62-9, Triglycidyl isocyanurate 4986-89-4, Pentaerythritol tetraacrylate 25068-38-6, Epikote 1004 **97649-40-6D**, [4-(Phenylsulfonyl)phenylsulfonyl]acetic acid, salt with amine 136168-27-9D, Guanidine, N,N'''-1,2-ethanediylbis[N',N''-dicyclohexyl-, salt with acetic acid derivative
(**lithog.** printing plate **precursor** and
method for printing plate making using the same)

L29 ANSWER 12 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2003:768384 HCAPLUS
DOCUMENT NUMBER: 139:283398
TITLE: Photopolymerizable composition suitable for manufacturing light-sensitive direct-imaging **lithographic** printing plate **precursor**
INVENTOR(S): Kunita, Kazuto; Kondo, Shunichi
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 100 pp.
CODEN: JKXXAF
DOCUMENT TYPE: **Patent**
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003280187	A2	20031002	JP 2002-83561	2002 0325

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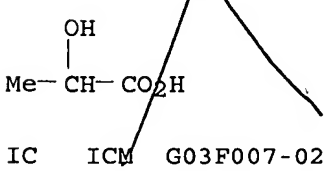
PRIORITY APPLN. INFO.: JP 2002-83561 2002 0325
<--

OTHER SOURCE(S): MARPAT 139:283398
AB The title composition contains compound (Q1)k-R-(Q2)m (Q1-2 = CH2=C(Z)COO-R1-NHCO2-, CH2=C(COX2)CH(Ra)-OCO-R2-OCONH-; Z = H, CH3, alkyl; R1-2 aliphatic hydrocarbon; Ra = H, hydrocarbon; R = n-valent hydrocarbon; 2≤n = k+m≤6 integer; k = 0-6 integer; m = 0-6 integer). The composition provides printing plates precursors of high sensitivity and good storageability and printing plates of high printing durability.
IT **50-21-5**, 2-Hydroxypropionic acid, reactions
(photopolymerizable composition suitable for manufacturing light-sensitive **lithog.** printing plate **precursor**)
RN 50-21-5 HCAPLUS
CN Propanoic acid, 2-hydroxy- (9CI) (CA INDEX NAME)



IC ICM G03F007-027

ICS C08F020-34; C08F022-22; G03F007-00
CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
ST photopolymerizable compn manufg **lithog** printing plate **precursor**
IT Light-sensitive materials
Lithographic plates
(photopolymerizable composition suitable for manufacturing light-sensitive **lithog.** printing plate **precursor**)
IT 607388-55-6P
(m pphotopolymerizable composition suitable for manufacturing light-sensitive **lithog.** printing plate **precursor**)
IT **50-21-5**, 2-Hydroxypropionic acid, reactions 822-06-0, Hexamethylenediisocyanate 7426-71-3, Trimethylolbutane 30674-80-7, 2-(Methacryloyloxy)ethyl isocyanate
(photopolymerizable composition suitable for manufacturing light-sensitive **lithog.** printing plate **precursor**)
IT 51265-15-7P 102338-03-4P 361176-51-4P 607388-48-7P
607388-49-8P 607388-50-1P 607388-51-2P 607388-52-3P
607388-53-4P 607388-54-5P 607388-56-7P 607388-57-8P
607388-58-9P 607388-59-0P 607388-60-3P 607388-61-4P
607388-62-5P 607388-63-6P 607388-64-7P 607388-65-8P
607388-66-9P 607388-67-0P
(photopolymerizable composition suitable for manufacturing light-sensitive **lithog.** printing plate **precursor**)

L29 ANSWER 13 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2003:757173 HCAPLUS
DOCUMENT NUMBER: 139:268033
TITLE: Thermally-convertible **lithographic** printing **precursor** developable with aqueous medium
INVENTOR(S): Goodin, Jonathan W.; Emans, John; Christall, Keith; Yu, Yisong; Rademacher, Katja
PATENT ASSIGNEE(S): USA
SOURCE: U.S. Pat. Appl. Publ., 13 pp., Cont.-in-part of U. S. Ser. No. 909,791, abandoned.
CODEN: USXXCO
DOCUMENT TYPE: **Patent**
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 11
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2003180658	A1	20030925	US 2003-347836	2003 0122
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US 2002081526	A1	20020627	US 2000-745520	2000 1226
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US 6589710	B2	20030708		
US 2002081519	A1	20020627	US 2000-745548	2000 1226
			<--	

US 6605407 B2 20030812
US 2002155374 A1 20021024 US 2001-785339
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US 2002187428 A1 20021212 US 2001-785338
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US 2003017416 A1 20030123 US 2001-909777
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US 2003017417 A1 20030123 US 2001-909791
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US 2003017410 A1 20030123 US 2001-909964
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WO 2004066029 A2 20040805 WO 2003-CA1155
2003
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CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI,
GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG,
KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK,
MN, MW, MX, MZ, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU,
SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA,
UG, US, UZ, VC, VN, YU, ZA, ZM, ZW
RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM,
AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ,
DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL,
PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN,
GQ, GW, ML, MR, NE, SN, TD, TG
AU 2003254664 A1 20040813 AU 2003-254664
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PRIORITY APPLN. INFO.: US 2000-745520 A2
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US 2000-745548 A2
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US 2001-785338 B2
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US 2001-785339 B2
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0220

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US	2001-909777	A2	20010723
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US	2001-909791	B2	20010723
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US	2001-909792	A2	20010723
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US	2001-909964	B2	20010723
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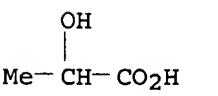
US	2003-347836	A	20030122
<--			
WO	2003-CA1155	W	20030730
<--			

AB A **lithog.** printing **precursor** for **lithog.** offset printing comprises a layer of imageable medium on a hydrophilic base. The imageable medium comprises hydrophobic polymer particles in an aqueous medium, a substance for converting light into heat, and a non-crosslinkable aqueous-soluble composition The **lithog.** printing **precursor** may be used to make lithog. printing surfaces that obtain long run lengths on lower quality paper and in the presence of press-room chems. The **lithog.** printing **precursor** can be imaged and developed on-press and the imageable medium and can also be sprayed onto a hydrophilic surface to create a printing surface that may be processed wholly on-press. It can also be processed in the more conventional fully off-press fashion. The hydrophilic surface can be a printing plate substrate or the printing cylinder of a printing press or a sleeve around the printing cylinder of a printing press. The cylinder can be conventional or seamless.

IT **50-21-5**, DL-Lactic acid, uses **60-00-4**, Ethylenediaminetetraacetic acid, uses **77-92-9**, Citric acid, uses
(thermally-convertible **lithog.** printing **precursor** developable with aqueous medium)

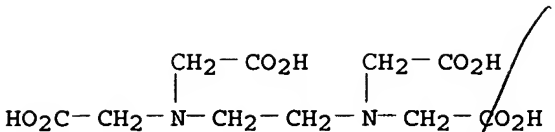
RN 50-21-5 HCAPLUS

CN Propanoic acid, 2-hydroxy- (9CI) (CA INDEX NAME)

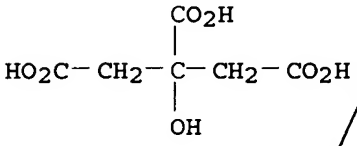


RN 60-00-4 HCAPLUS

CN Glycine, N,N'-1,2-ethanediylbis[N-(carboxymethyl)- (9CI) (CA INDEX NAME)



RN 77-92-9 HCAPLUS
CN 1,2,3-Propanetricarboxylic acid, 2-hydroxy- (9CI) (CA INDEX NAME)



IC ICM G03F007-038
ICS G03F007-09; G03F007-30
INCL 430270100; 430138000; 430275100; 430278100; 430281100; 430286100; 430302000; 430309000; 430348000; 430401000
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
ST thermally convertible **lithog** printing plate **precursor** aq developable
IT Lithographic plates
(thermally-convertible **lithog.** printing **precursor** developable with aqueous medium)
IT Carbon black, uses
(thermally-convertible **lithog.** printing **precursor** developable with aqueous medium)
IT **50-21-5**, DL-Lactic acid, uses **60-00-4**, Ethylenediaminetetraacetic acid, uses **77-92-9**, Citric acid, uses 109-07-9, 2-Methylpiperazine 110-85-0, Piperazine, uses 141-82-2, Malonic acid, uses 497-19-8, Sodium carbonate, uses 557-34-6, Zinc acetate 7632-05-5, Sodium phosphate 14024-63-6, Zinc acetylacetonate 14220-26-9, Copper acetylacetonate 26400-93-1 40530-01-6, Rhoplex WL 91 116788-76-2, Rhoplex WL-51 134127-48-3, ADS 830A 365276-78-4, Flexbond 289 438462-36-3, Texigel 13-800 438462-37-4, UCAR 471 438462-38-5, HG-1630 485831-81-0, Xenacryl 2651 603952-77-8, ADS 830WS
(thermally-convertible **lithog.** printing **precursor** developable with aqueous medium)

L29 ANSWER 14 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2003:711895 HCAPLUS
DOCUMENT NUMBER: 139:237758
TITLE: Manufacture of lithographic plate by development of heat-mode precursor by using rubber solution
INVENTOR(S): Van Hunsel, Johan; Vermeersh, Joan; Kokkelenberg, Dirk
PATENT ASSIGNEE(S): Agfa Gevaert N.V., Belg.
SOURCE: Jpn. Kokai Tokkyo Koho, 9 pp.
CODEN: JKXXAF
DOCUMENT TYPE: **Patent**
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

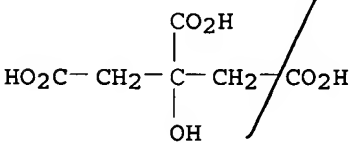
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003255527	A2	20030910	JP 2003-56973 <--	2003 0304
EP 1586448	A1	20051019	EP 2005-104140 <--	2002 0306
R: BE, DE, FR, GB, NL				
US 2003170570	A1	20030911	US 2003-379362 <--	2003 0304
PRIORITY APPLN. INFO.:			EP 2002-100226 A <--	2002 0306
			US 2002-366884P P <--	2002 0322

AB The lithog. plate is manufactured from a heat mode precursor having a surface coating layer containing hydrophilic thermoplastic polymer particles on a hydrophilic support surface by (a) exposing of the precursor to heat so that the polymer particles are coagulated on the exposed region and (b) applying of a rubber solution for development by removal of the masked region. The precursor can be developed and gummed up by the single step.

IT **77-92-9**, Citric acid, uses
(development and gumming up of heat mode **lithog.** plate **precursor** by rubber solution containing)

RN 77-92-9 HCAPLUS

CN 1,2,3-Propanetricarboxylic acid, 2-hydroxy- (9CI) (CA INDEX NAME)



IC ICM G03F007-004
ICS G03F007-00

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38, 39, 41, 46

IT Surfactants
(development and gumming up of heat mode **lithog.** plate **precursor** by rubber solution containing)

IT Lithographic plates
(development and gumming up of heat mode **lithog.** plate **precursor** in single step)

IT Synthetic rubber, processes
(development and gumming up of heat mode **lithog.** plate **precursor** in single step)

IT IR radiation
(development and gumming up of heat mode **lithog.** plate **precursor** in single step after exposure to)
IT Coating materials
(hydrophilic coatings, containing thermoplastic polymer particles; development and gumming up of heat mode **lithog.** plate **precursor** having)
IT 68-04-2, TriSodium citrate **77-92-9**, Citric acid, uses
866-83-1, Monopotassium citrate
(development and gumming up of heat mode **lithog.** plate **precursor** by rubber solution containing)
IT 140214-49-9 221661-29-6
(development and gumming up of heat mode **lithog.** plate **precursor** having coating containing)
IT 9003-01-4, Poly(acrylic acid)
(development and gumming up of heat mode **lithog.** plate **precursor** having coating containing)
IT 9003-53-6, Polystyrene 9003-54-7, Acrylonitrile-styrene copolymer
(particles; development and gumming up of heat mode **lithog.** plate **precursor** having coating containing)
IT 58318-10-8, Dowfax 3B2
(surfactant; development and gumming up of heat mode **lithog.** plate **precursor** by rubber solution containing)

L29 ANSWER 15 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2003:511924 HCAPLUS
DOCUMENT NUMBER: 139:76381
TITLE: High speed negative-working thermal printing plates
INVENTOR(S): Munnelly, Heidi M.; West, Paul R.; Saraiya, Shashikant; Huang, Jian Bing
PATENT ASSIGNEE(S): Kodak Polychrome Graphics, LLC, USA
SOURCE: U.S. Pat. Appl. Publ., 13 pp., Cont.-in-part of U.S. Ser. No. 40,241.
CODEN: USXXCO
DOCUMENT TYPE: **Patent**
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 4
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2003124460	A1	20030703	US 2002-217005	20020812
US 6893797	B2	20050517	<--	
US 6309792	B1	20011030	US 2000-690898	20001017
US 2003118939	A1	20030626	<-- US 2001-40241	20011109
JP 2003012713	A2	20030115	<-- JP 2002-107119	

2002
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US 2002197564 A1 20021226 US 2002-131866
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US 6884568 B2 20050426
WO 2003091022 A1 20031106 WO 2003-EP4271
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W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA,
CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI,
GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG,
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MN, MW, MX, MZ, NO, NZ, OM, PH, PL, PT, RO, RU, SC, SD,
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VN, YU, ZA, ZM, ZW
RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM,
AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ,
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PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN,
GQ, GW, ML, MR, NE, SN, TD, TG
AU 2003233055 A1 20031110 AU 2003-233055
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JP 2005523484 T2 20050804 JP 2003-587621
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WO 2004014652 A1 20040219 WO 2003-US24782
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RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM,
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AU 2003261453 A1 20040225 AU 2003-261453
2003
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JP 2005535471 T2 20051124 JP 2004-527863
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US 2004259027 A1 20041223 US 2004-847708
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PRIORITY APPLN. INFO.:

US 2001-40241	A2	2001 1109
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WO 2000-EP1349	A1	2000 0218
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US 2000-690898	A2	2000 1017
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US 2001-832989	A	2001 0411
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US 2002-66874	A2	2002 0204
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US 2002-131866	A	2002 0425
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US 2002-217005	A	2002 0812
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US 2002-283757	B2	2002 1030
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WO 2003-EP4271	W	2003 0424
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WO 2003-US24782	W	2003 0807
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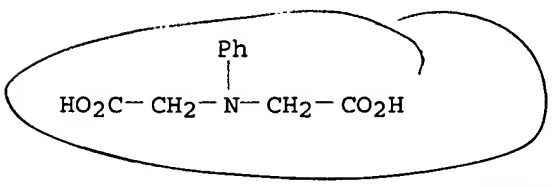
OTHER SOURCE(S): MARPAT 139:76381

AB Neg. working thermally imageable elements useful as **lithog** . printing plate **precursors** and methods for their use are disclosed. The elements have a substrate, a layer of imageable composition over the substrate, and, optionally, an overcoat layer over the layer of imageable composition The imageable composition has an allyl-functional polymeric binder. Optimum resolution and on-press performance can be attained without a post-exposure bake. The elements do not require a post-exposure bake and can be used in on-press development applications.

IT **1137-73-1**, N-Phenyliminodiacetic acid
(high speed neg.-working thermal printing plates containing)

RN 1137-73-1 HCAPLUS

CN Glycine, N-(carboxymethyl)-N-phenyl- (9CI) (CA INDEX NAME)



IC ICM G03F007-031
ICS G03F007-105; G03F007-038; G03F007-26
INCL 430273100; 430944000; 430300000; 430302000; 430945000; 430964000; 430287100; 430284100; 101457000; 101453000
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
IT **1137-73-1**, N-Phenyliminodiacetic acid 3584-23-4, 2-(4-Methoxyphenyl)-4,6-bis(trichloromethyl)-s-triazine 3712-60-5, 2-(4-Chlorophenyl)-4,6-bis(trichloromethyl)-s-triazine 6542-67-2, 2,4,6-Tris(trichloromethyl)-s-triazine 24504-22-1, 2-Phenyl-4,6-bistrichloromethyl)-s-triazine 24687-55-6, 2,4,6-Tris(tribromomethyl)-s-triazine 95735-63-0, (3,4-Dimethoxyphenylthio)acetic acid 115965-96-3, Airvol 203 117482-71-0, 2-(4-Methylth iophenyl)-4,6-bis(trichloromethyl)-1,3,5-triazine 161279-62-5, Joncryl 683
(high speed neg.-working thermal printing plates containing)
REFERENCE COUNT: 30 THERE ARE 30 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L29 ANSWER 16 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2003:97350 HCAPLUS
DOCUMENT NUMBER: 138:145102
TITLE: Thermally-convertible **lithographic** printing **precursor** and imageable medium with coalescence inhibitor
INVENTOR(S): Goodin, Jonathan W.; Emans, John; Christall, Keith; Yu, Yisong; Rademacher, Katja
PATENT ASSIGNEE(S): Creo Inc., Can.
SOURCE: PCT Int. Appl., 58 pp.
CODEN: PIXXD2
DOCUMENT TYPE: **Patent**
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 11
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2003010006	A1	20030206	WO 2002-CA943	2002 0625

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RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG

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PRIORITY APPLN. INFO.:	US 2001-909777	A	2001 0723
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	US 2001-909964	A	2001 0723
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	US 2002-177754	A	2002 0624
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	US 2002-177755	A	2002 0624
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	US 2002-177771	A	2002 0624
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	US 2000-745520	A2	2000

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US 2000-745548 A2
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US 2001-785338 B2
2001
0220
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US 2001-785339 B2
2001
0220
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WO 2002-CA943 W
2002
0625
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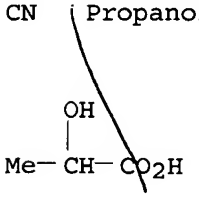
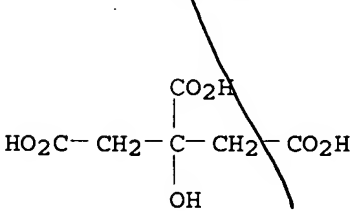
AB The present invention relates to a **lithog.** printing **precursor** for **lithog.** offset printing comprising a layer of imageable medium on a hydrophilic base. The imageable medium comprises hydrophobic polymer particles in an aqueous medium, a substance for converting light into heat, and a coalescence inhibitor. The **lithog.** printing **precursor** may be used to make lithog. printing surfaces that obtain long run lengths on lower quality paper and in the presence of press-room chems. The **lithog.** printing **precursor** can be imaged and developed on-press and the imageable medium can also be sprayed onto a hydrophilic surface to create a printing surface that may be processed wholly on-press. It can also be processed in the more conventional fully off-press fashion. The hydrophilic surface can be a printing plate substrate or the printing cylinder of a printing press or a sleeve around the printing cylinder of a printing press. The cylinder can be conventional or seamless.

IT **50-21-5**, DL-Lactic acid, uses **77-92-9**, Citric acid, uses
(thermally-convertible **lithog.** printing **precursor** with coalescence inhibitor)

RN 50-21-5 HCAPLUS
CN Propanoic acid, 2-hydroxy- (9CI) (CA INDEX NAME)



RN 77-92-9 HCAPLUS
CN 1,2,3-Propanetricarboxylic acid, 2-hydroxy- (9CI) (CA INDEX NAME)



IC ICM B41C001-10
ICS B41M005-36

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
ST thermally convertible **lithog** printing **precursor** coalescence inhibitor
IT Lithographic plates
(offset; thermally-convertible **lithog.** printing **precursor** with coalescence inhibitor)
IT Coalescence
Lithographic plates
(thermally-convertible **lithog.** printing **precursor** with coalescence inhibitor)
IT **50-21-5**, DL-Lactic acid, uses 64-02-8, Ethylenediaminetetraacetic acid, tetra sodium salt **77-92-9**, Citric acid, uses 109-07-9, 2-Methylpiperazine 110-85-0, Piperazine, uses 141-82-2, Malonic acid, uses 497-19-8, Sodium carbonate, uses 557-34-6, Zinc acetate 7601-54-9, Sodium phosphate 14024-48-7 14024-63-6, Zinc acetylacetonate 14220-26-9, Copper acetylacetonate 27360-85-6 40530-01-6, Rhoplex WL91 116788-76-2, Rhoplex WL51 365276-78-4, Flexbond 289 438462-36-3, Texigel 13-800 438462-37-4, Ucar 471 438462-38-5, HG-1630 485831-81-0, Xenacryl 2651
(thermally-convertible **lithog.** printing **precursor** with coalescence inhibitor)
REFERENCE COUNT: 5 THERE ARE 5 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L29 ANSWER 17 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2003:58675 HCAPLUS
DOCUMENT NUMBER: 138:115097
TITLE: Thermally convertible **lithographic** printing **precursor** comprising an organic acid
INVENTOR(S): Emans, John; Goodin, Jonathan William; Yu, Yisong; Rademacher, Katja
PATENT ASSIGNEE(S): UK
SOURCE: U.S. Pat. Appl. Publ., 9 pp.
CODEN: USXXCO
DOCUMENT TYPE: **Patent**
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 11
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2003017410	A1	20030123	US 2001-909964	20010723
US 2003207210	A1	20031106	US 2002-177771	20020624
WO 2003010006	A1	20030206	WO 2002-CA943	20020625

W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA,

CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI,
GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG,
KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK,
MN, MW, MX, MZ, NO, NZ, OM, PH, PL, PT, RO, RU, SD, SE,
SG, SI, SK, SL, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ,
VN, YU, ZA, ZM, ZW
RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AT,
BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC,
NL, PT, SE, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW,
ML, MR, NE, SN, TD, TG

EP 1409250 A1 20040421 EP 2002-740170
2002
0625
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R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE,
MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR

US 2003180658 A1 20030925 US 2003-347836
2003
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PRIORITY APPLN. INFO.: US 2000-745520 A2
2000
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US 2000-745548 A2
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US 2001-785338 B2
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US 2001-785339 B2
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US 2001-909777 B2
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US 2001-909791 B2
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US 2001-909792 A2
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US 2001-909964 B2
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US 2002-177754 A
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US 2002-177755 A
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US 2002-177771 A 2002 0624
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WO 2002-CA943 W 2002 0625
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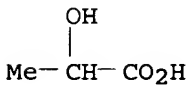
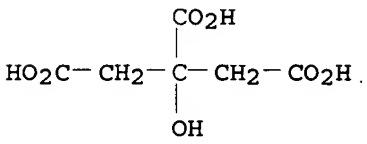
AB The present invention provides an imaging element for lithog. offset printing comprising hydrophobic polymer particles in an aqueous medium, a substance for converting light into heat and an organic acid. The imaging element may be used for printing long run lengths on lower quality paper and in the presence of set-off powder. The imaging element may be imaged and developed on-press and may be sprayed onto a hydrophilic surface to create a printing surface that may be processed wholly on-press. The hydrophilic surface may be a printing plate substrate or the printing cylinder of a printing press or a seam less sleeve around the printing cylinder of a printing press. This cylinder may be conventional or seam less.

IT **50-21-5**, DL-Lactic acid, uses **77-92-9**, Citric acid, uses
(thermally convertible **lithog.** printing **precursor** comprising organic acid and)

RN 50-21-5 HCAPLUS
CN Propanoic acid, 2-hydroxy- (9CI) (CA INDEX NAME)



RN 77-92-9 HCAPLUS
CN 1,2,3-Propanetricarboxylic acid, 2-hydroxy- (9CI) (CA INDEX NAME)



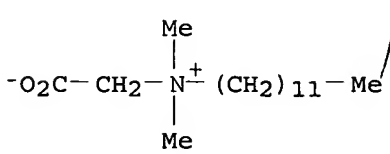
IC ICM G03F007-038
ICS B41N001-00; B41N003-00
INCL 430270100; 101453000
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
ST thermally convertible **lithog** printing **precursor** org acid
IT Lithographic plates
(offset; thermally convertible **lithog.** printing **precursor** comprising organic acid)
IT Polyesters, uses
Polyurethanes, uses
(thermoplastic polymer; thermally convertible **lithog.** printing **precursor** comprising organic acid and)
IT **50-21-5**, DL-Lactic acid, uses **77-92-9**, Citric

acid, uses 141-82-2, Malonic acid, uses 194491-31-1
(thermally convertible **lithog.** printing **precursor** comprising organic acid and)
IT 9002-86-2, Polyvinylchloride 9002-88-4, Polyethylene
9003-53-6, Polystyrene 25014-41-9, Polyacrylonitrile
116788-76-2, Rhoplex WL51 365276-78-4, Flexbond 289
438462-36-3, Texigel 13-800 485831-81-0, Xenacryl 2651
(thermoplastic polymer; thermally convertible **lithog.** printing **precursor** comprising organic acid and)

L29 ANSWER 18 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2003:40253 HCAPLUS
DOCUMENT NUMBER: 138:115077
TITLE: IR-sensitive directly imaging **lithographic** plate **precursors** containing surfactant in undercoat layer and/or backcoat layer
INVENTOR(S): Takamiya, Shuichi
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 38 pp.
CODEN: JKXXAF
DOCUMENT TYPE: **Patent**
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003015307	A2	20030117	JP 2001-197924 <--	2001 0629
PRIORITY APPLN. INFO.:			JP 2001-197924 <--	2001 0629

AB The title precursor has an undercoat layer and an image-forming layer on a support with a backcoat layer, wherein the undercoat layer and/or backcoat layer contain nonionic, anionic, or cationic surfactants. The printing plate precursor provides sharp clear images.
IT **683-10-3**
(surfactant; IR-sensitive directly imaging **lithog.** plate **precursors**)
RN 683-10-3 HCAPLUS
CN 1-Dodecanaminium, N-(carboxymethyl)-N,N-dimethyl-, inner salt (9CI) (CA INDEX NAME)



IC ICM G03F007-11
ICS B41N001-14; G03F007-00; G03F007-09
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and

Other Reprographic Processes)
ST IR **lithog** plate **precursor** surfactant undercoat layer back
IT Light-sensitive materials
Lithographic plates
Surfactants
(IR-sensitive directly imaging **lithog.** plate **precursors**)
IT Polyoxyalkylenes, uses
(surfactant; IR-sensitive directly imaging **lithog.** plate **precursors**)
IT 64-20-0 71-91-0 **683-10-3** 1643-19-2 1941-30-6
3546-96-1 9002-92-0 9004-78-8 9004-95-9 9005-00-9
9040-05-5 14356-62-8 16527-85-8 17066-08-9 25322-68-3
27252-75-1 35545-57-4 63442-13-7 96107-79-8 486436-93-5
(surfactant; IR-sensitive directly imaging **lithog.** plate **precursors**)

L29 ANSWER 19 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2002:736760 HCAPLUS
DOCUMENT NUMBER: 137:255398
TITLE: Lithographic heat sensitive printing plate precursors
INVENTOR(S): Kitteridge, John Michael
PATENT ASSIGNEE(S): Agfa-Gevaert, Belg.
SOURCE: U.S. Pat. Appl. Publ., 7 pp.
CODEN: USXXCO
DOCUMENT TYPE: **Patent**
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2002136985	A1	20020926	US 2002-47580 <--	20020115
EP 1225039	A1	20020724	EP 2001-2 <--	20010124

R: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LI, LU, MC, NL, PT, SE, TR

PRIORITY APPLN. INFO.:		
EP 2001-200230 <--	A	20010123
EP 2001-2 <--	A	20010124
US 2001-270439P <--	P	20010221

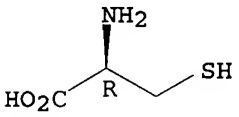
AB A **lithog.** printing plate **precursor** comprises a grained and anodized aluminum substrate coated with a metallic layer, preferably a silver layer, on top of which is applied a

layer comprising at least one oleophilising agent and at least one hydrophilic stain-reducing agent, the hydrophilic agent being chosen such that it adsorbs onto the metallic layer but is not so strongly adsorbed thereon as to displace the oleophilising agent. Preferably, the oleophilising agent comprises a mercaptotetrazole or mercaptooxadiazole derivative, the hydrophilic stain-reducing agent comprises a material which includes at least one sulfur, selenium or tellurium containing group, and the layer addnl. comprises an addnl. hydrophilic material. The invention provides **lithog.** printing plate **precursors** which may be image-wise exposed by means of a high intensity laser beam to provide press ready plates showing reduced stain in non-image areas, high image quality, good press properties and high durability on press without the requirement for the use of intermediate film and developer chemical

IT **52-90-4**, L-Cysteine, uses **56-89-3**, L-Cystine, uses **70-49-5**, 2-Mercaptosuccinic acid
(hydrophilic stain-reducing agent; lithog. heat sensitive printing plate precursors)

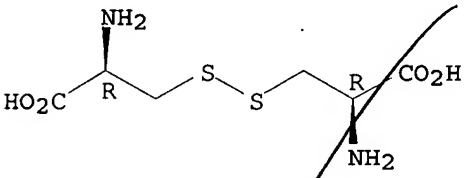
RN 52-90-4 HCAPLUS
CN L-Cysteine (9CI) (CA INDEX NAME)

Absolute stereochemistry.

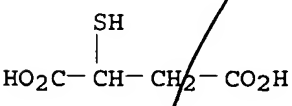


RN 56-89-3 HCAPLUS
CN L-Cystine (9CI) (CA INDEX NAME)

Absolute stereochemistry.



RN 70-49-5 HCAPLUS
CN Butanedioic acid, mercapto- (9CI) (CA INDEX NAME)



IC ICM G03F007-004
ICS G03F007-06; G03F007-11; G03F007-36; G03F007-40
INCL 430276100
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
IT **52-90-4**, L-Cysteine, uses **56-89-3**, L-Cystine, uses **70-49-5**, 2-Mercaptosuccinic acid 147-93-3, Thiosalicylic acid 333-20-0, Potassium thiocyanate 7772-98-7,

Sodium thiosulphate
(hydrophilic stain-reducing agent; lithog. heat sensitive printing plate precursors)

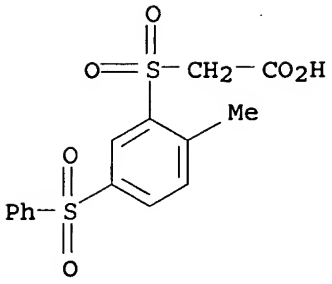
L29 ANSWER 20 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2002:673036 HCAPLUS
DOCUMENT NUMBER: 137:224143
TITLE: On-press-developable lithographic master plates showing good printing durability and background whiteness
INVENTOR(S): Sakata, Itaru
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 46 pp.
CODEN: JKXXAF
DOCUMENT TYPE: **Patent**
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002251004	A2	20020906	JP 2001-46870 <--	2001 0222
PRIORITY APPLN. INFO.:			JP 2001-46870 <--	2001 0222

OTHER SOURCE(S): MARPAT 137:224143
AB The plates, suited for heat-mode laser recording, comprise hydrophilic supports and image-forming layers containing blocked polyisocyanates, heat- or radiation-sensitive ≥2-valent base precursors, and optionally photothermal converters. The base precursors may be R(SO2CH2CO2H)x [R = alkyl, aryl, (O-, S-, SO-, or SO2-bridged) alkylene or arylene, mono- or bivalent heterocyclic residue; x = 1, 2].
IT **457048-29-2P 457048-30-5P 457048-31-6P**
(base **precursors**; on-press-developable **lithog**. master plates showing good printing durability and background whiteness)
RN 457048-29-2 HCAPLUS
CN Acetic acid, [[2-methyl-5-(phenylsulfonyl)phenyl]sulfonyl]-, compd. with N,N'''-1,2-ethanediylbis[guanidine] (2:1) (9CI) (CA INDEX NAME)

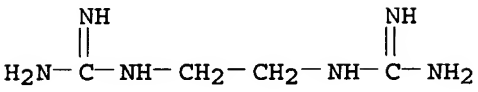
CM 1

CRN 303750-25-6
CMF C15 H14 O6 S2



CM 2

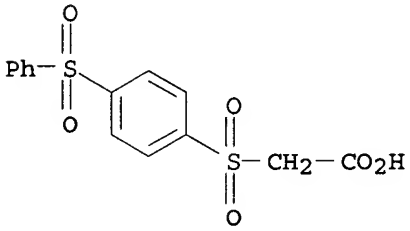
CRN 44956-51-6
CMF C4 H12 N6



RN 457048-30-5 HCAPLUS
CN Acetic acid, [[4-(phenylsulfonyl)phenyl]sulfonyl]-, compd. with N,N''',N''''''-(nitrilotri-2,1-ethanediyl)tris[guanidine] (3:1) (9CI) (CA INDEX NAME)

CM 1

CRN 97649-40-6
CMF C14 H12 O6 S2



CM 2

CRN 73571-48-9
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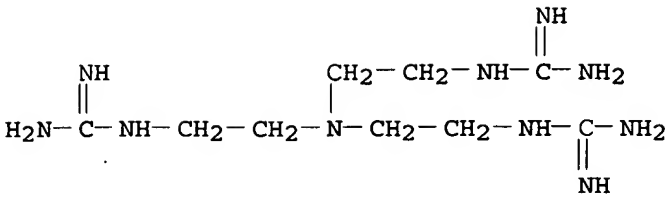
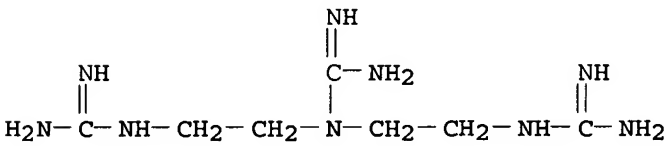


RN 457048-31-6 HCAPLUS
CN Acetic acid, [[4-(phenylsulfonyl)phenyl]sulfonyl]-, compd. with N,N-bis[2-[(aminoiminomethyl)amino]ethyl]guanidine (3:1) (9CI) (CA INDEX NAME)

CM 1

CRN 457048-24-7
CMF C7 H19 N9



CM 2

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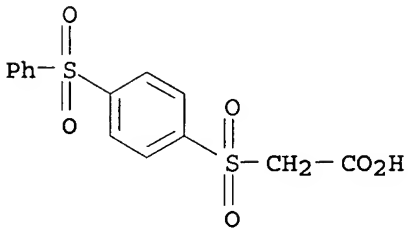
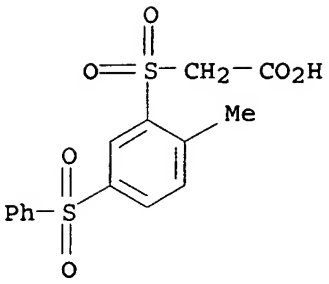


IT **303750-25-6**
(in preparation of polyvalent base **precursors** for presensitized **lithog.** master plates)
RN 303750-25-6 HCAPLUS
CN Acetic acid, [[2-methyl-5-(phenylsulfonyl)phenyl]sulfonyl]- (9CI) (CA INDEX NAME)



IC ICM G03F007-004
ICS G03F007-004; B41N001-14; C08G018-30; C08G018-80; G03F007-00
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
IT **457048-29-2P 457048-30-5P 457048-31-6P**
(base **precursors**; on-press-developable **lithog**
. master plates showing good printing durability and background whiteness)
IT 44956-51-6 **303750-25-6**
(in preparation of polyvalent base **precursors** for presensitized **lithog.** master plates)

L29 ANSWER 21 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2002:503361 HCAPLUS
DOCUMENT NUMBER: 137:70529
TITLE: **Lithographic** printing plate **precursor**
INVENTOR(S): Tomita, Tadabumi; Teraoka, Katsuyuki; Hotta, Hisashi; Matsuura, Atsushi; Uesugi, Akio
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Eur. Pat. Appl., 83 pp.
CODEN: EPXXDW
DOCUMENT TYPE: **Patent**
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 1219464	A2	20020703	EP 2001-130269	2001 1220
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EP 1219464	A3	20040616		
R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR				
JP 2002214764	A2	20020731	JP 2001-9871	2001 0118
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JP 2002365791	A2	20021218	JP 2001-206572	2001 0706
			<--	
US 2002182538	A1	20021205	US 2001-22244	

2001
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US 6890700 B2 20050510
PRIORITY APPLN. INFO.: JP 2000-387210 A
2000
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JP 2001-9871 A
2001
0118
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JP 2001-104632 A
2001
0403
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JP 2001-206572 A
2001
0706
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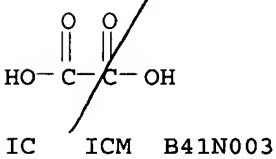
AB The **lithog.** printing plate **precursor** comprises a metal support having an anodic oxide film formed on it, and an image-forming layer containing a light-to-heat converting agent, or a light-sensitive layer capable of image-forming with IR laser exposure. The mouth diameter of the surface of the pores of the anodic oxide film on the metal support is 0-30 nm and the maximum inside diameter is 20-300 nm. Preferably, a particle layer is provided between the anodic oxide film and the heat-sensitive layer in a thermal type **lithog.** printing plate **precursor** so that heat can be efficiently used in image forming. The disclosed precursor has improved residual color and residual film, excellent smearing resistance and press life, and high sensitivity.

IT **144-62-7**, Oxalic acid, uses
(surface of aluminum substrate for **lithog.** printing plate **precursor** treated with anodic oxidation using)

RN 144-62-7 HCAPLUS

CN Ethanedioic acid (9CI) (CA INDEX NAME)



IC ICM B41N003-03

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

ST **lithog** printing plate **precursor** aluminum substrate surface treatment

IT Etching
Lithographic plates
Surface roughness
Surface treatment
(metal substrate for **lithog.** printing plate **precursor** with special surface treatment)

IT Anodization
(metal substrate for **lithog.** printing plate **precursor** with special surface treatment including)

IT 5496-71-9, Cyasorb IR 165 22371-56-8, NK 3508 134127-48-3

(Ir absorbant used in imaging layer of **lithog.** printing plate **precursor**)
IT 13870-30-9, Disodium trisilicate
(hydrophilization treatment for aluminum substrate of **lithog.** printing plate **precursor** using)
IT 1344-28-1, Alumina, uses
(particle layer on aluminum substrate of **lithog.** printing plate **precursor** containing)
IT 7429-90-5, Aluminum, uses
(substrate for **lithog.** printing plate **precursor**)
IT 1310-73-2, Sodium hydroxide, uses 7697-37-2, Nitric acid, uses
(surface of aluminum substrate for **lithog.** printing plate **precursor** treated with)
IT **144-62-7**, Oxalic acid, uses 7664-38-2, Phosphoric acid, uses 7664-93-9, Sulfuric acid, uses
(surface of aluminum substrate for **lithog.** printing plate **precursor** treated with anodic oxidation using)
IT 10043-35-3, Boric acid, uses 10101-97-0, Nickel sulfate hexahydrate
(surface sealing treatment solution for aluminum substrate of **lithog.** printing plate **precursor** containing)

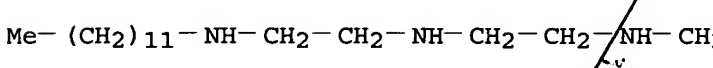
L29 ANSWER 22 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2002:236333 HCAPLUS
DOCUMENT NUMBER: 136:270631
TITLE: Method for making lithographic plates from light-sensitive **lithographic** plate **precursor** having aluminum support
INVENTOR(S): Kondo, Shunichi; Nagase, Hiroyuki
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 13 pp.
CODEN: JKXXAF
DOCUMENT TYPE: **Patent**
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002091017	A2	20020327	JP 2000-279892	2000 0914
			<--	
PRIORITY APPLN. INFO.:			JP 2000-279892	2000 0914
			<--	

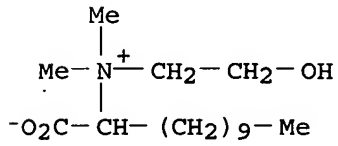
AB The title method includes the steps of: imagewise exposing a **lithog.** plate **precursor** having a light-sensitive layer containing ethylenic polymerizing compds., a photopolymn. initiator, and a polymer binder on a support; and developing the printing plate precursor with a developing solution containing an inorg. alkali and surfactants, wherein the surfactants consist of a nonionic surfactant with a polyoxyalkylene ether group and an amphoteric surfactant. The method, which uses the nonionic surfactant in the developing solution, provides the safety for the lithog. process making and the good lithog. plate characteristics.
IT **6843-97-6 93673-07-5 133119-64-9**

405217-13-2
(surfactant in developing solution for lithog. plate)

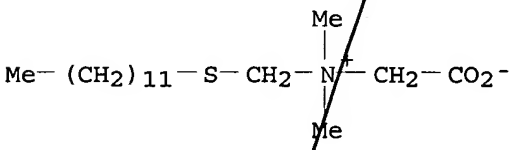
RN 6843-97-6 HCAPLUS
CN Glycine, N-[2-[[2-(dodecylamino)ethyl]amino]ethyl]- (6CI, 7CI, 8CI, 9CI) (CA INDEX NAME)



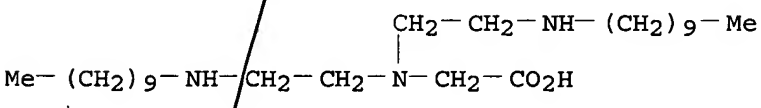
RN 93673-07-5 HCAPLUS
CN 1-Undecanaminium, 1-carboxy-N-(2-hydroxyethyl)-N,N-dimethyl-, inner salt (9CI) (CA INDEX NAME)



RN 133119-64-9 HCAPLUS
CN Methanaminium, 1-carboxy-N-[(dodecylthio)methyl]-N,N-dimethyl-, inner salt (9CI) (CA INDEX NAME)



RN 405217-13-2 HCAPLUS
CN Glycine, N,N-bis[2-(decylamino)ethyl]- (9CI) (CA INDEX NAME)



IC ICM G03F007-32
ICS G03F007-00
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
ST safety lithog plate light sensitive **lithog precursor** aluminum support
IT Surfactants
(amphoteric; method for making lithog. plates from light-sensitive **lithog.** plate **precursor** with aluminum support)
IT Lithographic plates
Photoimaging
(method for making lithog. plates from light-sensitive **lithog.** plate **precursor** with aluminum support)
IT Surfactants
(nonionic; method for making lithog. plates from

light-sensitive **lithog.** plate **precursor** with aluminum support)

IT **6843-97-6** 9004-78-8, Polyoxyethylene phenyl ether 35138-81-9, Polyoxyethylene methyl phenyl ether 69778-08-1 76169-11-4, Lipomin LA **93673-07-5 133119-64-9** **405217-13-2**
(surfactant in developing solution for lithog. plate)

L29 ANSWER 23 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2002:63926 HCAPLUS
DOCUMENT NUMBER: 136:126608
TITLE: Silver halide diffusion-transfer **lithographic** printing plate **precursor** having aluminum support and method for making printing plate therefrom
INVENTOR(S): Hirata, Kenji; Tsubakii, Yasuo
PATENT ASSIGNEE(S): Mitsubishi Paper Mills, Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 9 pp.
CODEN: JKXXAF
DOCUMENT TYPE: **Patent**
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2002023377	A2	20020123	JP 2000-212564	2000 0713

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PRIORITY APPLN. INFO.: JP 2000-212564 2000 0713

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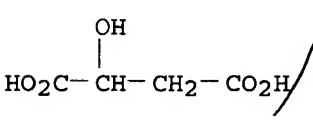
AB The invention relates to a silver halide diffusion-transfer **lithog.** printing plate **precursor** having an Al support, wherein the printing plate precursor contains an organic carboxylic acid in at least one layer on the support. The printing plate precursor, which contains the organic carboxylic acid, generates little etch pit.

IT **6915-15-7**, Malic acid
(organic carboxylic acid in **lithog.** printing plate **precursor**)

RN 6915-15-7 HCAPLUS
CN Butanedioic acid, hydroxy- (9CI) (CA INDEX NAME)



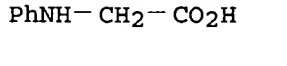
IC ICM G03F007-07
ICS G03C008-06; G03F007-00; G03F007-40
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
IT Lithographic plates
(silver halide diffusion-transfer **lithog.** printing plate **precursor** having aluminum support according to

and method for making printing plate therefrom)
IT 77-92-9, Citric acid, uses 110-15-6, Succinic acid, uses 124-04-9, Adipic acid, uses **6915-15-7**, Malic acid
(organic carboxylic acid in **lithog.** printing plate **precursor**)

L29 ANSWER 24 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2001:435467 HCAPLUS
DOCUMENT NUMBER: 135:53518
TITLE: Heat-sensitive **lithographic** printing plate **precursor** for IR-laser exposure
INVENTOR(S): Kita, Nobuyuki; Maemoto, Kazuo
PATENT ASSIGNEE(S): Japan
SOURCE: U.S. Pat. Appl. Publ., 11 pp.
CODEN: USXXCO
DOCUMENT TYPE: **Patent**
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2001003643	A1	20010614	US 2000-729350	2000 1205 <--
US 6576397	B2	20030610		
JP 2001166459	A2	20010622	JP 1999-346317	1999 1206 <--
PRIORITY APPLN. INFO.:			JP 1999-346317	A 1999 1206 <--

AB A heat-sensitive **lithog.** printing plate **precursor** comprises a thermal polymerization layer, which contains an aqueous alkali-soluble polymer having addition polymerizable unsatd. bonds at the side chains and a thermal polymerization initiator, and a water-soluble overcoat layer, which has a water-soluble polymer and a compound capable of converting light into heat, on a support, which has a hydrophilic surface. The **lithog.** printing plate **precursor**, which contains thermal polymerizing materials, is handled in a bright room.
IT **103-01-5**, N-Phenylglycine
(thermal polymerization layer in heat-sensitive **lithog.** printing plate **precursor**)
RN 103-01-5 HCAPLUS
CN Glycine, N-phenyl- (6CI, 7CI, 8CI, 9CI) (CA INDEX NAME)



IC ICM G03C007-00
ICS G03C001-73; G03C001-77; G03F007-11
INCL 430273100
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and

Other Reprographic Processes)
ST heat sensitive **lithog** printing plate **precursor**
IR laser exposure
IT Lithographic plates
(heat-sensitive **lithog.** printing plate **precursor** for IR-laser exposure)
IT Polymerization
(thermal; heat-sensitive **lithog.** printing plate **precursor** for IR-laser exposure)
IT 90216-38-9P, Allyl methacrylate-methacrylic acid copolymer 102772-82-7P, Methyl methacrylate-ethyl methacrylate-methacrylic acid-acrylonitrile copolymer
(thermal polymerization layer in heat-sensitive **lithog.** printing plate **precursor**)
IT **103-01-5**, N-Phenylglycine 147-14-8, Copper β-phthalocyanine 150-76-5, p-Methoxyphenol 1707-68-2, 2-(o-Chlorophenyl)-4,5-diphenylimidazolyl dimer 4986-89-4, Pentaerythritol tetraacrylate 33943-20-3, Di-tert-butyl peroxyisophthalate 77473-08-6, 3,3',4,4'-Tetrakis(tert-butylperoxycarbonyl)benzophenone
(thermal polymerization layer in heat-sensitive **lithog.** printing plate **precursor**)

L29 ANSWER 25 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 2000:822999 HCAPLUS
DOCUMENT NUMBER: 133:367836
TITLE: Photosensitive polyimide **precursor** compositions for **lithographic** formation of peeling-resistant patterns
INVENTOR(S): Yuba, Tomoyuki; Yoshimura, Toshio
PATENT ASSIGNEE(S): Toray Industries, Inc., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 12 pp.
CODEN: JKXXAF
DOCUMENT TYPE: **Patent**
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2000321770	A2	20001124	JP 1999-133908	1999 0514 <--

PRIORITY APPLN. INFO.: JP 1999-133908 1999 0514 <--

AB The polyimide precursors in the compns. have structural repeating unit [COR1(CO2R3)2CONHR2NH] (I; R1 = tetravalent C≥2 organic group; R2 = divalent C≥2 organic group; R3 = H, alkali metal, ammonium, C1-30 organic group) containing 1-45 mol% of those with di-Ph ether [(C6H3)2O] as R1 and the photo-crosslinking groups in the compns. is 40-450 mol% of structural repeating unit I. Optionally, the compns. may also contain R4NR5R6 (R4-6 = C1-30 organic groups with at least 1 containing an ethylenically unsatd. group). The compns. are useful in fabrication of semiconductor devices and multilayer printed circuits.
IT **103-01-5**, N-Phenylglycine

(photoinitiator; photosensitive polyimide precursors containing di-Ph ether tetracarboxylic acid for formation of peeling-resistant patterns)
RN 103-01-5 HCAPLUS
CN Glycine, N-phenyl- (6CI, 7CI, 8CI, 9CI) (CA INDEX NAME)

IC ICM G03F007-038
ICS C08G073-10; G03F007-037; H01L021-027
CC 74-4 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 38
IT **103-01-5**, N-Phenylglycine
(photoinitiator; photosensitive polyimide precursors containing di-Ph ether tetracarboxylic acid for formation of peeling-resistant patterns)

L29 ANSWER 26 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 1998:806584 HCAPLUS
DOCUMENT NUMBER: 130:73883
TITLE: Method of preparing lithographic plate
INVENTOR(S): Watkiss, Philip John
PATENT ASSIGNEE(S): Agfa-Gevaert Naamloze Vennootschap, Belg.
SOURCE: PCT Int. Appl., 20 pp.
CODEN: PIXXD2
DOCUMENT TYPE: **Patent**
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 9855309	A1	19981210	WO 1998-EP3481	1998 0603 <--
W: JP, US RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE				
GB 2325892	A1	19981209	GB 1998-11835	1998 0603 <--
EP 986476	A1	20000322	EP 1998-937460	1998 0603 <--
EP 986476	B1	20011128		
R: DE, FR, GB, IT, NL				
JP 2002508853	T2	20020319	JP 1999-501590	1998 0603 <--
US 6183936	B1	20010206	US 2000-445074	2000 0207

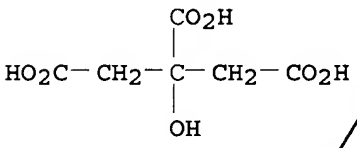
PRIORITY APPLN. INFO.: GB 1997-11385 A 1997 0603
WO 1998-EP3481 W 1998 0603

AB A method of preparing a lithog. plate involves providing a plate precursor comprising a grained and anodized aluminum substrate coated with a metallic silver layer, imagewise exposing the precursor by means of a high-intensity laser beam, and treating the plate by chemical and mech. means in order to remove stains on the plate surface. On exposure of the plate precursor, removal of the metallic silver layer occurs in the exposed areas. The method provides a press-ready lithog. plate free of background stains, which gives a clean, even appearance in exposed areas and shows high image resolution and excellent durability on press, while eliminating the requirement for the use of an intermediate film and a chemical developer.

IT **77-92-9**, Citric acid, uses
(IR laser-sensitive aluminum **lithog.** plate **precursors** with silver layers treated by compns. containing)

RN 77-92-9 HCAPLUS

CN 1,2,3-Propanetricarboxylic acid, 2-hydroxy- (9CI) (CA INDEX NAME)



IC ICM B41C001-10
ICS G03F007-06

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

ST laser **lithog** plate **precursor** stain removal

IT **Lithographic** plates
(**precursors**, IR laser-sensitive; with aluminum substrates and silver layers treated by chemical and mech. means to remove stains)

IT 7440-22-4, Silver, uses
(IR laser-sensitive aluminum **lithog.** plate **precursors** with silver layers treated by chemical and mech. means to remove stains)

IT 64-02-8, Tetrasodium ethylenediaminetetraacetate **77-92-9**, Citric acid, uses 86-93-1 102-71-6, Triethanolamine, uses 10139-51-2, Ceric ammonium nitrate 70253-99-5 95507-75-8, Lutensit AP-S
(IR laser-sensitive aluminum **lithog.** plate **precursors** with silver layers treated by compns. containing)

IT 7429-90-5, Aluminum, uses
(IR laser-sensitive **lithog.** plate **precursors** with silver layers and treated by chemical and mech. means to remove stains)

REFERENCE COUNT: 9 THERE ARE 9 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L29 ANSWER 27 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 1998:545684 HCAPLUS
DOCUMENT NUMBER: 129:209364
TITLE: Lithographic original plate capable of direct platemaking using infrared laser
INVENTOR(S): Kawamura, Koichi; Kitatani, Katsushi; Kobayashi, Fumikazu; Maemoto, Kazuo
PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 13 pp.
CODEN: JKXXAF
DOCUMENT TYPE: **Patent**
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 4
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 10221842	A2	19980821	JP 1997-26877 <--	19970210
JP 3751703	B2	20060301		
US 6017677	A	20000125	US 1998-12596 <--	19980123

PRIORITY APPLN. INFO.:
JP 1997-10755 A 19970124 <--
JP 1997-26877 A 19970210 <--
JP 1997-26878 A 19970210 <--
JP 1997-36665 A 19970220 <--

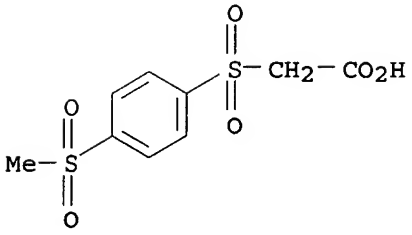
AB The title original plate comprises a support coated with a recording layer containing a polymer having functional groups that generates a sulfonic acid by the action of base in its side chain and a heat-base-generating agent. The original plate is capable of direct platemaking from digital data by using IR laser and forming images without wet development process and the resulting printing plate shows high printing durability.

IT **100906-66-9**
(lithog. original plate containing base precursor and polymer having sulfonic acid-generating group)

RN 100906-66-9 HCAPLUS
CN Acetic acid, [[4-(methylsulfonyl)phenyl]sulfonyl]-, compd. with guanidine (1:1) (9CI) (CA INDEX NAME)

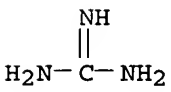
CM 1

CRN 100906-65-8
CMF C9 H10 O6 S2



CM 2

CRN 113-00-8
CMF C H5 N3



IC ICM G03F007-004
ICS B41C001-055; B41N001-14; G03F007-00; G03F007-033
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
ST **lithog** plate platemaking base **precursor**; polymer sulfonic acid generating group lithog
IT 5150-56-1, Guanidine trichloroacetate **100906-66-9**
(lithog. original plate containing base precursor and polymer having sulfonic acid-generating group)

L29 ANSWER 28 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 1996:138278 HCAPLUS
DOCUMENT NUMBER: 124:216182
TITLE: Photosensitive material for diffusion-transfer lithographic plate
INVENTOR(S): Yokoie, Hiroaki; Endo, Akihiro
PATENT ASSIGNEE(S): Fuji Photo Film Co Ltd, Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 17 pp.
CODEN: JKXXAF
DOCUMENT TYPE: **Patent**
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 3
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 07333832	A2	19951222	JP 1994-152813	19940610

<--

US 5554482 A 19960910 US 1995-428892 1995 0425

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PRIORITY APPLN. INFO.: JP 1994-109031 A 1994 0425

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JP 1994-128194 A 1994 0518

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JP 1994-152813 A 1994 0610

<--

AB In the material having ≥2 layers containing a Ag halide, a reductant, a polymerizable compound or crosslinkable polymer, and a base precursor (X) on a support, the X-containing layer further contains a block copolymer consisting of vinyl alc. units (Y) and more hydrophobic units than Y. A lithog. printing plate obtained from the material gives high-resolution images.

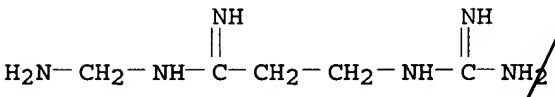
IT **174675-99-1**
(base precursor; photosensitive material containing vinyl alc.-based block copolymer for thermodevelopable diffusion-transfer lithog. plate)

RN 174675-99-1 HCAPLUS

CN Acetic acid, [[4-(phenylsulfonyl)phenyl]sulfonyl]-, compd. with 3-[(aminoiminomethyl)amino]-N-(aminomethyl)propanimidamide (2:1) (9CI) (CA INDEX NAME)

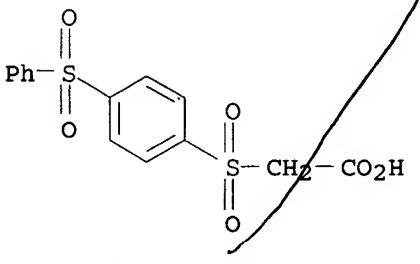
CM 1

CRN 174675-98-0
CMF C5 H14 N6



CM 2

CRN 97649-40-6
CMF C14 H12 O6 S2



IC ICM G03F007-00

ICS G03F007-004; G03F007-06
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
ST lithog printing plate photosensitive silver halide; thermodevelopable lithog plate block copolymer; diffusion transfer **lithog** plate base **precursor**
IT **174675-99-1**
(base precursor; photosensitive material containing vinyl alc.-based block copolymer for thermodevelopable diffusion-transfer lithog. plate)

L29 ANSWER 29 OF 29 HCAPLUS COPYRIGHT 2006 ACS on STN
ACCESSION NUMBER: 1994:422566 HCAPLUS
DOCUMENT NUMBER: 121:22566
TITLE: Manufacture of electrophotographic **lithographic** plate **precursor**
INVENTOR(S): Oda, Akihisa; Kato, Eiichi; Tashiro, Hiroshi
PATENT ASSIGNEE(S): Fuji Photo Film Co Ltd, Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 33 pp.
CODEN: JKXXAF
DOCUMENT TYPE: **Patent**
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 3
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 05072757	A2	19930326	JP 1991-234526 <--	19910913
US 5250376	A	19931005	US 1992-943520 <--	19920911

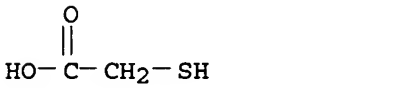
PRIORITY APPLN. INFO.:
JP 1991-234526 A 19910913 <--
JP 1991-266398 A 19911015 <--
JP 1991-297244 A 19911113 <--

AB The title plate precursor is made using an electrophotog. photoreceptor in which ≥1 photoconductive layer(s) containing an inorg. photoconductive compound and a binder resin is formed on an elec. conductive support; the title manufacture comprises the steps of imagewise exposure of the photoreceptor having the binder resin containing ≥1 resin(s) containing ≥1 kind(s) of polymer components having functional groups CO2CH(X)(X') (X, X' = at least 1 of them is an electron-withdrawing group; the sum of their Hammett σp values is >0.45) to form an electrostatic latent image on the photoreceptor, developing the latent image to form a toner image, and desensitizing the nonimage area of the photoconductive layer with a processing solution containing at least a

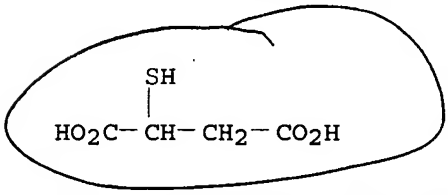
hydrophilic compound containing a substituent(s) having a Pearson nucleophilic reactivity constant n >5.5. The desensitization can be effected easily in a short time and the plate precursor shows storage stability even under severe conditions.

IT **68-11-1**, Thioglycolic acid, uses **70-49-5**, Thiomalic acid **111857-77-3**
(desensitization solution containing, for manufacture of electrophotog. **lithog.** plate **precursor**)

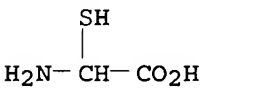
RN 68-11-1 HCAPLUS
CN Acetic acid, mercapto- (8CI, 9CI) (CA INDEX NAME)



RN 70-49-5 HCAPLUS
CN Butanedioic acid, mercapto- (9CI) (CA INDEX NAME)



RN 111857-77-3 HCAPLUS
CN Acetic acid, aminomercapto- (9CI) (CA INDEX NAME)



IC ICM G03G005-05
ICS B41N001-08; B41N003-08; G03G005-08; G03G005-085; G03G013-28

CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35

ST electrophotog **lithog** plate **precursor** manuf; binder resin electrophotog lithog plate; desensitization soln electrophotog lithog plate

IT **68-11-1**, Thioglycolic acid, uses **70-49-5**, Thiomalic acid 107-35-7, Taurine 111-42-2, Diethanolamine, uses 141-43-5, uses 147-93-3, Thiosalicylic acid 3375-50-6, 2-Mercaptoethanesulfonic acid 7757-83-7, Sodium sulfite 7772-98-7, Sodium thiosulfate 10196-04-0, Ammonium sulfite 43064-23-9, 2-Mercaptoethylphosphonic acid **111857-77-3** 145024-19-7
(desensitization solution containing, for manufacture of electrophotog. **lithog.** plate **precursor**)